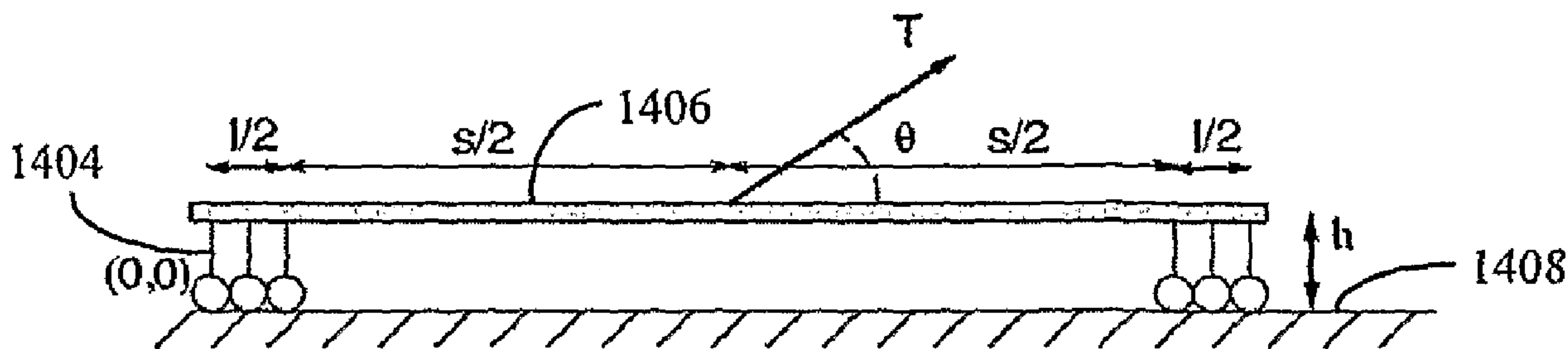




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 (54) Title: CONTROLLING PEEL STRENGTH OF MICRON-SCALE STRUCTURES



(57) **Abrégé/Abstract:**

A fabricated microstructure includes a base and one or more nano-structures disposed on one or more portions of the base to adhere to a contact surface. The one or more portions of the base with the one or more nano-structures are located on the base such that, when the one or more nano-structures adhere to the contact surface and an external force is applied to peel the base from the contact surface, the one or more nano-structures in the one or more portions of the base facilitate or resist peeling of the nano-structures from the contact surface.

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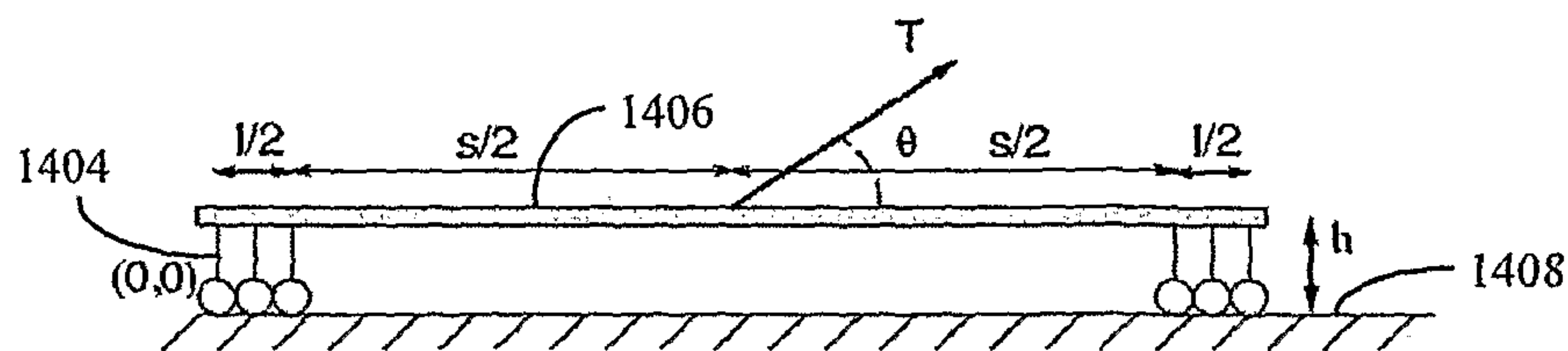
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(54) Title: CONTROLLING PEEL STRENGTH OF MICRON-SCALE STRUCTURES



(57) Abstract: A fabricated microstructure includes a base and one or more nano-structures disposed on one or more portions of the base to adhere to a contact surface. The one or more portions of the base with the one or more nano-structures are located on the base such that, when the one or more nano-structures adhere to the contact surface and an external force is applied to peel the base from the contact surface, the one or more nano-structures in the one or more portions of the base facilitate or resist peeling of the nano-structures from the contact surface.



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**CONTROLLING PEEL STRENGTH OF MICRON-SCALE STRUCTURES****CROSS REFERENCE TO RELATED APPLICATION**

**[0001]** The present Application is a continuation-in-part of U.S. Patent Application Serial No. 10/655,271, filed September 3, 2003, which is a continuation of U.S. Patent Application Serial No. 09/644,936, filed August 23, 2000, now Patent No. 6,737,160, which claims the benefit of provisional Application 60/172,731, filed December 20, 1999. All of the previously mentioned Applications are incorporated herein by reference in their entirety.

**STATEMENT REGARDING FEDERALLY SPONSORED  
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**[0002]** This invention was made with government support under Contract No. N66001-00-C-8047 and N6600101-C-8072 awarded by Defense Advanced Research Projects Agency (DARPA) and Contract No. NIRT EEC-0304730 awarded by National Science Foundation (NSF). The government has certain rights in the invention.

**BACKGROUND****1. Field**

**[0003]** The present application relates generally to the fabrication and utilization of micron-scale structures. More particularly, this application relates to controlling peel strength of micron-scale structures.

**2. Related Art**

**[0004]** There is an ongoing need for improved adhesives. Improved adhesives have applications ranging from everyday aspects of life (e.g., tape, fasteners, and toys) to high technology (e.g., removal of microscopic particles from semiconductor wafers, transporting fiber optic devices, and assembly of sub-mm mechanisms, particularly those including micro-fabricated components, or components that cannot tolerate grippers, adhesives, or vacuum manipulators).

**[0005]** Adhesive mechanisms in nature have been studied, but have not been fully understood or exploited. For example, Geckos are exceptional in their ability to rapidly climb up

smooth vertical surfaces. The mechanism of adhesion used in Geckos, Anolis lizards, some skinks, and some insects, has been debated for nearly a century.

[0006] While some prior work has identified the morphology of seta used by Geckos and other insects, this prior work does not identify how the seta operates. In addition, this prior work fails to identify how to use a seta to perform useful work.

[0007] It would be highly desirable to identify and exploit the adhesive force mechanism utilized by Geckos and other insects. Such information could result in the utilization of new adhesive microstructures and the fabrication of such structures.

### SUMMARY

[0008] In one exemplary embodiment, a fabricated microstructure includes a base and one or more nano-structures disposed on one or more portions of the base to adhere to a contact surface. The one or more portions of the base with the one or more nano-structures are located on the base such that, when the one or more nano-structures adhere to the contact surface and an external force is applied to peel the base from the contact surface, the one or more nano-structures in the one or more portions of the base facilitate or resist peeling of the nano-structures from the contact surface.

### BRIEF DESCRIPTION OF THE FIGURES

[0009] FIG. 1A illustrates preloading operations performed in accordance with an embodiment of the invention.

[0010] FIG. 1B illustrates rows of setae used in accordance with the invention.

[0011] FIG. 1C illustrates a single seta used in accordance with the invention.

[0012] FIG. 1D is an enlarged view of a single seta used in accordance with an embodiment of the invention.

[0013] FIG. 1E is an enlarged view of a single extended surface spatula on a spatula stalk, in accordance with an embodiment of the invention.

[0014] FIG. 1F is an enlarged view of a single extended surface spatula on a spatula stalk, in accordance with an embodiment of the invention.

[0015] FIG. 1G illustrates an array of spatulae formed at the end of a shaft to form seta used in accordance with the invention.

[0016] FIG. 1H illustrates a system to measure adhesive force achieved in accordance with the invention.

[0017] FIG. 1I is another illustration of a system to measure adhesive force achieved in accordance with the invention.

[0018] FIG. 2A-2B illustrate different forces, as a function of time, associated with the loading and adhesion operation of a structure of the invention.

[0019] FIG. 3 illustrates perpendicular preload force associated with an embodiment of the invention.

[0020] FIG. 4 illustrates perpendicular force during detachment of a structure utilized in accordance with the invention.

[0021] FIG. 5A-5C illustrate the fabrication of an array of setae with spatula structures in accordance with an oxide/nitride fabrication process utilized in accordance with an embodiment of the invention.

[0022] FIG. 6A-6B illustrate the fabrication of an array of setae in accordance with an excitation source process utilized in accordance with an embodiment of the invention.

[0023] FIG. 7 illustrates the fabrication of an array of setae with spatula structures in accordance with a stalk and seeding process utilized in accordance with an embodiment of the invention.

[0024] FIG. 8 illustrates the fabrication of a single spatula using a micro-pipette.

[0025] FIG. 9 illustrates an embossing tool used to form a spatulae mold for use in accordance with an embodiment of the invention.

[0026] FIG. 10A-10D illustrate lithographically induced self-construction of spatulae in accordance with an embodiment of the invention.

[0027] FIG. 11A-11B illustrate a roller nano-imprinting technique that may be used to form spatulae in accordance with an embodiment of the invention.

[0028] FIG. 12 illustrates a two-layer photoresist fabrication technique that may be used in accordance with an embodiment of the invention.

[0029] FIG. 13 illustrates a setae-based manipulator that may be used in accordance with an embodiment of the invention.

[0030] FIG. 14 illustrates a fabricated micron-sized structure with nano-structures disposed on a base.

[0031] FIG. 15 illustrates the results of an experiment to measure the force of detachment of a seta.

[0032] FIG. 16 illustrates a fabricated micron-sized structure with nano-structures disposed on a portion of a base.

[0033] FIG. 17 illustrates the maximum pure tensile force needed before a nano-structure slides or peels.

[0034] FIG. 18 illustrates a fabricated micron-sized structure with nano-structures disposed on portions of a base in opposing locations on the base.

[0035] FIG. 19 illustrates the maximum pure force needed before a nano-structure slides or peels.

[0036] Like reference numerals refer to corresponding parts throughout the drawings.

## DETAILED DESCRIPTION

[0037] The following description sets forth numerous specific configurations, parameters, and the like. It should be recognized, however, that such description is not intended as a limitation on the scope of the present invention or applications thereof, but instead provides examples and illustrations.

[0038] The invention is directed toward the use of micron scale structures to achieve adhesion. In particular, the invention uses a seta structure. The seta structure has a shaft. Positioned at the end of the shaft is a spatula or an array of spatulae. Adhesion is produced as the spatula or array of spatulas produce intimate contact with a surface.

[0039] In general, the shaft is between 1 and 500 microns long, preferably approximately 10 to 100 microns long. The diameter of the shaft is preferably between 0.01 and 0.1 times the length of the shaft, preferably approximately 0.05 times the length of the shaft.

[0040] The terminal end of the shaft has at least one spatula. Preferably, the terminal end of the shaft has between 1 and 1000 spatulae. The array of spatulae is preferably less than 10 microns wide, preferably approximately 1 micron wide. Preferably, each spatula of the array of spatulae has an extended surface at its terminal end. The extended surface may be in the form of a paddle or a curved segment of a sphere, as shown below.

[0041] The structure of the invention is modeled from structures found in nature, such as the seta found on the foot of a Tokay gecko (*Gekko gecko*). Many species of gecko (e.g., clade Gekkonoidea), species of *Anolis*, and several skink species have adhesive setae that may also be used in accordance with the invention. In addition, beetles and kissing-bugs have setae that may be used in accordance with the invention. The invention is implemented with natural or fabricated setae, as discussed below.

[0042] Examples of seta structures found in nature follow. The seta of a Tokay Gecko has a stalk (shaft) diameter of  $5\mu$ , a stalk height of  $110\mu$ , a tip (spatulae) length of  $0.2\mu$ , a tip width of  $0.2\mu$ , and between 100-1000 tips, where the total tip area per stalk is 2 to  $20\mu^2$ , *Anolis cuvieri* has a stalk diameter of  $0.5\mu$ , a stalk height of  $22\mu$ , a tip length of  $0.6\mu$ , a tip width of  $0.7\mu$ , and between 100-1000 tips, where the total tip area per stalk is 2 to  $20\mu^2$ . *Prasinohaema virens*

(skink) has a stalk diameter of  $2\mu$ , a stalk height of  $26\mu$ , a tip length of  $6\mu$ , a tip width of  $7\mu$ , and between 100-1000 tips, where the total tip area per stalk is approximately  $20\mu^2$ .

[0043] By way of example, FIG. 1A illustrates a Tokay gecko 20 with terminal limbs 21 that have naturally occurring setae. The live gecko 20 is restrained. The cuticular layer of a portion of a terminal limb (e.g., a toe) 21 is removed. This operation, analogous to cutting hair, allows the gecko to harmlessly regenerate its setae. It has been demonstrated that hundreds or thousands of setae can be easily harvested without sacrificing the living being from which the setae are removed.

[0044] After removal, the cuticular surface is scraped to break off individual seta, preferably at the base of the shaft of the seta. FIG. 1B illustrates rows 22 of setae associated with the gecko 20. FIG. 1C illustrates the shaft 24 of a single seta 26. The figure also illustrates the spatulae 28 positioned at the end of the shaft 24.

[0045] FIG. 1D is an enlarged view of a single seta 26. The figure illustrates that the shaft 24 is roughly perpendicular to the spatulae 28.

[0046] FIG. 1E is an enlarged view of a single spatula 29 on a spatula stalk 30. The spatula stalk 30 may be the shaft 24 or a separate tendril extending from the shaft 24. Preferably, each spatula 29 has an extended surface. In FIG. 1E, the extended surface is in the form of a paddle structure. In FIG. 1F, the extended surface is in the form of a sphere. FIG. 1G is an enlarged view of an array of spatulae 28.

[0047] The realization of large adhesive forces by the setae is contingent upon preload operations performed in accordance with the invention. Detachment of the setae occurs at a characteristic angle, as specified in accordance with the invention. FIG. 1H illustrates a substrate (i.e., a sensor 32) that was used to characterize these forces. FIG. 1I illustrates the characteristic angle ( $\alpha$ ) for detaching setae of the invention. The characteristic angle ( $\alpha$ ) is formed between the seta 26 and a surface 40 to which the seta is attached.

[0048] The inventors have identified that the adhesive force of a seta depends upon its three-dimensional orientation (spatulae pointing toward or away from the surface) and the extent to which the seta is preloaded (pushed into and pulled along the surface) during initial contact.



Contacting the surface with the seta in a direction other than with spatulae projecting toward the surface resulted in forces less than  $0.3 \mu\text{N}$  when the seta was pulled away perpendicular to the surface. A pull parallel to the surface showed that the force produced by the inactive, non-spatular region increased with normal or perpendicular force, typical of a material with a coefficient of friction equal to 0.2. By contrast, when the active spatular region was projecting toward the surface, force increased by 20 to 60-fold. The force resulting from pulling the seta parallel to the surface during attachment increased when setae were first pushed toward the surface, providing a perpendicular preloading force. This initial perpendicular force need not be maintained during the subsequent pull. Setal force parallel to the surface increased linearly with the perpendicular preloading force.

[0049] Experiments in which seta were pulled away from the surface of a wire demonstrated that perpendicular preloading alone is insufficient to prevent the seta from being dislodged easily. Seta that were first pushed into the surface and then pulled parallel to it developed over ten times the force ( $13.6 \mu\text{N} \pm 2.6 \text{ SD}$ ;  $N=17$ ) upon being pulled away from the surface than those having only a perpendicular preload ( $0.6 \mu\text{N} \pm 0.7 \text{ SD}$ ;  $N=17$ ). The largest parallel forces were observed only following a few microns of sliding. The results of preloading on setal force production suggest that a small perpendicular preloading force in concert with a rearward displacement or parallel preload may be necessary to "engage" adhesion. Preloading is believed to increase the number of spatulae contacting the surface.

[0050] The orientation of the setae is also important in detachment. The force produced when a seta was pulled away from the surface was not significantly differently from the force measured during a pull parallel to the surface if the same perpendicular preload was given. However, it has been identified that setae detached at a similar angle ( $30.6^\circ \pm 1.8 \text{ SD}$ ;  $N=17$ ) and force when pulled away from the sensor's surface. To check for the presence of a critical angle of detachment, the perpendicular force was held constant, while the setal angle was progressively increased until detachment. Setal angle at detachment changed by only 15% over a range of perpendicular forces. Thus, the invention utilizes a detachment angle of between  $35^\circ$  and  $25^\circ$ , preferably approximately  $30^\circ$ . The detachment angle values are based upon the disclosed seta structure in which the shaft of the seta is roughly perpendicular to the spatular surface, as shown

in FIG. 1D. Change in the orientation of the setae and perhaps even the geometry of the spatulae may facilitate detachment.

[0051] The foot of a Tokay gecko (*Gekko gecko*) holds approximately 5000 setae  $\text{mm}^{-2}$  and can produce 10 N of adhesive force with approximately 100  $\text{mm}^2$  of pad area. Therefore, each seta should produce an average force of 20  $\mu\text{N}$  and an average stress of 0.1  $\text{N mm}^{-2}$  ( $\sim 1$  atm). The actual magnitudes are probably greater, since it is unlikely that all setae adhere simultaneously.

[0052] The foregoing information is more fully appreciated in connection with specific operations performed in accordance with the invention. An isolated seta, secured by the technique discussed above, was glued to a substrate (e.g., to the end of a #2 insect pin) with epoxy (e.g., 5-MINUTE EPOXY sold by TTWDevcon, Danvers, Mass.). The pin had a diameter of approximately 15  $\mu\text{m}$ . To prevent the epoxy from creeping up the stalk of the seta, which might change the mechanical property of the specimen, the epoxy is preferably precured for approximately 1 minute before applying it to the specimen. All setae were oriented such that the active surface was approximately perpendicular to the axis of the pin. All preparations were completed under a compound microscope.

[0053] Force production by single, isolated seta during attachment was measured using a micromachined, dual-axis, piezoresistive sensor 32 of the type illustrated in FIG. 1H. The following discussion provides information with respect to the sensor 32. U.S. Pat. No. 5,959,200 describes a sensor of the type described herein. The sensor 32 does not form a part of the invention, rather it is merely used to obtain the performance results described below.

[0054] The cantilever sensor 32 of FIG. 1H was fabricated on a single-crystalline silicon wafer. The cantilever 32 has two independent force sensors, each with one predominant direction of compliance. The perpendicular force sensor consists of a thin triangular probe 50. The parallel force sensor is composed of four long slender ribs 52. A special 45° oblique ion implantation allowed piezoresistive and conductive regions to be implanted on both the parallel and perpendicular surfaces simultaneously. Forces applied to the tip of the sensor were resolved into these two orthogonal directions (parallel and perpendicular), and were measured by the changes in resistance of the piezoresistors. Since this device was originally designed for Atomic

Force Microscope data storage applications, each of these cantilever devices had a sharp tip near the vertex of its triangular probe. For the gecko setae adhesion measurement, the back-side of this device was used to provide a smooth surface for setal adhesion.

[0055] Each sets 26 was brought in contact with the sensor 32 by applying a small preload perpendicular to the surface to increase contact and induce adhesion. To determine the effect of preload force on submaximal parallel force, preload force was varied when setae were attached to the tip of the sensor, as shown in FIG. 3, which is discussed below. To measure maximal parallel force, the base of the triangular probe was used. Using the base increased area of contact, but did not allow for simultaneous measurement of preload forces. Sensor signals were taken while the seta was being pulled parallel to the surface by a piezoelectric manipulator at a rate of  $\sim 5 \mu\text{m sec}^{-1}$ . Sensor signals were amplified and filtered through a 300-Hz low-pass filter, and then digitized at 100 Hz using a 16-bit data acquisition card (Lab View<sup>TM</sup> on a PC). The collected data (in volts) were converted to deflections of the sensor through calibration constants, and multiplied by the stiffness of the cantilever to obtain force values.

[0056] Breaking or detachment force was defined as the maximal force a seta could exert perpendicular, or normal, to a surface immediately before it released. This value was determined for individual seta by measuring the amount it could displace a force gauge made from a 4.7 mm aluminum bonding wire with 25  $\mu\text{m}$  nominal diameter (American Fine Wire Corp., Selma, Ala.; the wire 40 is shown in FIG. 1I). To maximize contact area of the active surface of the seta to the wire, a 50  $\mu\text{m}$ .times.100  $\mu\text{m}$  section of the wire tip was flattened. The proximal end of the wire was fixed with epoxy onto a brass stub. The active surface of the seta was pressed against the flattened wire, producing a known perpendicular preload ( $1.6 \pm 0.25 \mu\text{N}$ ; means  $\pm$  SD). The force was measured using two different methods of detachment: (1) the seta was pulled normal to the wire; and (2) the insect pin was displaced  $19.7 \pm 3.45 \mu\text{m}$  along the wire to produce an additional parallel preload on the seta before pulling perpendicular or normal to the wire.

[0057] In all trials, detachment force was calculated from the maximum displacement of the wire pulled by the seta. All sequences were recorded with a video camera (e.g., a CCD camera sold by SONY) and digitized to a computer (e.g., an APPLE, MACINTOSH) using a video editing system (e.g., from MEDIA 100 Inc., Marlboro, Mass.). The initial position of the wire,

the angle of the seta with respect to the wire and the position of the wire at the point of separation were recorded and analyzed using image analysis software (e.g., NIH-Image software). The amount of deflection in the force gauge was converted to adhesion force after the force gauge was calibrated against standard weights.

[0058] The results of these operations are shown in FIG. 2-4. FIG. 2A illustrates forces associated with a perpendicular preload and a subsequent parallel pulling performed in accordance with the invention. As shown in FIG. 2A, setal adhesive force parallel to the surface increased linearly until the seta began to slide off the edge of the sensor at time  $t_x$ . If the seta was allowed to slide approximately 5  $\mu\text{m}$  along the sensor's surface, a distance imperceptible at the level of the foot, adhesive force continued to increase, as shown in FIG. 2B. The maximum adhesive force of single seta averaged  $194 \mu\text{N} \pm 25 \text{ SD}$  ( $N=28$ ), nearly 10-fold greater than predicted from whole animal estimates.

[0059] The single-seta force measurements suggest that if all setae were simultaneously and maximally attached, a single foot of a gecko could produce 100 N of adhesive force (-10 arm). Stated another way, the foot of a gecko could generate maximum observed force (10 N) with only 10% of its setae maximally attached.

[0060] The maximum force developed by a given seta could not be predicted from molecular interactions or microscopic anatomy alone. Setal force depended on its three-dimensional orientation (spatulae pointing toward or away from the surface) and the extent to which the hair was preloaded (i.e., pushed into and pulled along the surface) during initial contact. Contacting the surface with the seta in a direction other than with spatulas projecting toward the surface resulted in forces less than  $0.3 \mu\text{N}$  when the seta was pulled away perpendicular to the surface. A pull parallel to the surface showed that the force produced by the inactive, non-spatular region increased with normal or perpendicular force, typical of a material with a coefficient of friction equal to 0.25, see FIG. 3. By contrast, when the active spatular region was projecting toward the surface, force increased by 20 to 60-fold. The force resulting from pulling the seta parallel to the surface during attachment increased when setae were first pushed toward the surface providing a perpendicular preloading force, shown in FIG. 2A. This initial perpendicular force need not be maintained during the subsequent pull. Setal force parallel to the surface increased linearly with

the perpendicular preloading force, as shown in FIG. 3. Experiments in which seta were pulled away from a surface (e.g., surface 40, a wire in FIG. 1F) demonstrated that perpendicular preloading alone is insufficient to prevent the seta from being dislodged easily. Seta that were first pushed into the surface and then pulled parallel to it developed over ten times the force ( $13.6 \mu\text{N} \pm 2.6 \text{ SD}$ ;  $N=17$ ) upon being pulled away from the surface than those having only a perpendicular preload ( $0.6 \mu\text{N} \pm 0.7 \text{ SD}$ ;  $N=17$ ). The largest parallel forces were observed only following a few microns of sliding, as shown in FIG. 23.

**[0061]** The results of preloading on setal force production support the hypothesis that a small perpendicular preloading force in concert with a rearward displacement or parallel preload may be necessary to "engage" adhesion. Since the tips of the setae are directed rearwards away from the toenail, preloading may increase the number of spatulae contacting the surface.

**[0062]** The orientation of the setae also appears to be important in detachment during locomotion. The force produced when a seta was pulled away from the surface was not significantly different from the force measured during a pull parallel to the surface if the same perpendicular preload was given. However, it was identified that setae detached at a similar angle ( $30.6^\circ \pm 1.8 \text{ SD}$ ;  $N=17$ ) when pulled away from the wire sensor's surface. To check for the presence of a critical angle of detachment, perpendicular force was held constant, while the setal angle ( $\alpha$ ; FIG. 1F) progressively increased until detachment. Setal angle at detachment changed by only 15% over a range of perpendicular forces, as shown in FIG. 4. This observation is consistent with an adhesive model where sliding stops when pulling at greater than the critical setal angle and hence stress can increase at a boundary, causing fracture of the contact. Change in the orientation of the setae and perhaps even the geometry of the spatulae may facilitate detachment.

**[0063]** It has long been known that geckos peel the tips of their toes away from a smooth surface during running. Toe peeling may have two effects. First, it may put an individual seta in an orientation or at a critical angle that aids in its release. Second, toe peeling concentrates the detachment force on only a small subset of all attached setae at any instant. The toe peeling behavior is analogous to the technique used by humans to remove a piece of tape from a surface.

[0064] The direct setal force measurements are consistent with the hypothesis that adhesion in geckos is the result of intermolecular forces. The simple models available can only give the most approximate estimates of setal force production. If it is assumed that the tip of a spatula is a curved segment of a sphere (radius,  $R=2\ \mu\text{m}$ ) and is separated by a small distance from a large, flat surface where van der Waals forces become significant (atomic gap distance,  $D=0.3\ \text{nm}$ ), then setal force  $=AR/6D^2$ , where  $A$  is the material dependent Hamaker constant taken to be  $10^{-19}\ \text{J}^{10}$ . This estimate puts the van der Waals force for a spatula to be about  $0.4\ \mu\text{N}$ . Since the number of spatula per seta varies from 100 to 1000, setal force estimates range from 40 to 400  $\mu\text{N}$ .

[0065] Earlier experimental support for the van der Waals hypothesis comes from the observation that adhesive force of a whole gecko increases with increasing surface energy of the substrate. In addition, the rejection of alternative mechanisms such as suction, electrostatics, friction, microinterlocking, and wet adhesion, has been attempted. Adhesion experiments carried out in a vacuum and the disclosed measurements of greater than one atmosphere of adhesion pressure strongly suggest that suction is not involved. Experiments using X-ray bombardment eliminates electrostatic attraction as a mechanism necessary for setal adhesion, since the setae can still adhere in ionized air. Microinterlocking could function as a secondary mechanism, but the ability of geckos to adhere to polished glass shows that irregularities on the scale of the spatulae are not necessary for adhesion. The findings herein do not support a friction mechanism because the cantilever's surface is smooth (surface roughness less than or equal to  $2.5\ \text{nm}$ ) and the coefficient of friction of the setal keratin on silicon is low ( $\mu=0.25$ ; FIG. 3; dashed line). Capillary adhesion or glue are not likely mechanisms, since skin glands are not present on the feet of lizards. The mechanism of adhesion may involve a thin layer of water, or adsorbed water molecules on the seta and/or substrate.

[0066] Van der Waals forces are extremely weak at greater than atomic distance gaps, and require intimate contact between the adhesive and the surface. Polymeric adhesives such as tape are soft, and are able to deform sufficiently for intimate contact over a relatively large surface area. The feet of a Tokay gecko (*Gekko gecko*) contain approximately one billion spatulas that appear to provide a sufficiently large surface area in close contact with the substrate for adhesion to be the result of van der Waals forces.

[0067] As previously indicated, the invention may be used in connection with setae harvested from a live specimen. Alternately, the techniques of the invention may be used in connection with fabricated setae. Those skilled in the art will recognize a number of techniques that may be used to fabricate setae in accordance with the invention. For example, the devices may be fabricated through an oxide/nitride process, as shown in FIGS. 5A-5C.

[0068] Initially, a recess is etched in a semiconductor substrate. FIG. 5A illustrates a recess 101 formed in a semiconductor substrate 100. Nitride and oxide layers are then deposited on the substrate 100. FIG. 5A illustrates a nitride layer 102 and an oxide layer 104. The surface is then patterned and etched, resulting in the structure of FIG. 5B.

[0069] Afterwards, the underlying substrate 100 is etched, resulting in a well 106, as shown in FIG. 5C. At this point, the stress difference between the oxide and nitride layers causes the structure to curl from the plane defined by the substrate 100, thereby forming a shaft structure. The end of the shaft may then be roughened to form spatulae. For example, the spatulae may be formed by wet etching, radiation, plasma roughening, electrochemical etching, and the like. Alternately, a separate spatulae may be affixed to the shaft. Techniques for fabricating spatulas are discussed below.

[0070] Another technique that may be utilized in accordance with the invention exploits an excitation source. As shown in FIG. 6A, a sensitive material 122 is formed on a substrate 120. An excitation source 124 is used to apply excitation energy to the sensitive material 122. The deep-penetrating excitation alters the volume along the trajectory of excitation. The altered volume is then selectively etched away. This results in a tube 126, as shown in FIG. 6B. At higher densities of exposure, the remaining material becomes a random array of isolated fingers. The end of each tube 126 is then processed to form spatulae or spatulae are attached to the tubes.

[0071] FIG. 7 illustrates another technique that may be utilized in accordance with the invention. This embodiment relies upon the deposition of an etchable material on a substrate 130. Stalks 132 are then patterned and etched from the etchable material. The etched substrate may be coated with oxide and/or nitride layers. Alternately, polymer layers may be used as a coating. The polymer layers may be spin-cast, using materials, such as photoresist, polyimide,

glass, or epoxy-based compounds. The resultant stalks 132 are then seeded to form nanotubes 136, operating as spatulae.

[0072] Artificial spatulas may be formed using a glass micro-pipette drawn down to a narrow aperture (e.g., 500 nm) at an end. Liquid polymer is extruded through the hollow pipette and is then cured. Surface tension creates a hemispherical drop at the end of the pipette. FIG. 8 illustrates this technique. In particular, the figure illustrates a micro-pipette 150 with a liquid polymer 152 positioned therein to form a hemispherical drop 154.

[0073] Materials that can be applied to the micro-pipette include low viscosity ultra violet cure epoxy, uncured silicone rubber, or polyurethane resin. The hemisphere at the end of the micro-pipette can be flattened or embossed by pressing against a polished surface. A flattened surface, such as the paddle structure of FIG. 1F, with its larger contact area, has better adhesive properties than a sphere.

[0074] The single spatula pipette can be used as an embossing tool to make a nano-mold by plastically deforming a material, such as molten polystyrene. A large area mold (e.g., 20 by 20 microns) can be formed by either step-and-repeat embossing or by making an array of pipettes and embossing a large pattern.

[0075] FIG. 9 illustrates an array of pipettes used to form an embossing tool 160. The embossing tool 160 is applied to a polystyrene material 162 positioned on a substrate 164. This results in a patterned polystyrene surface 166.

[0076] Alternatively, a nano-channel glass, which consists of a large bundle of hollow glass fibers, can be used. The nano-channel glass can be filled with a polymer, and then the glass can be dissolved in an acid.

[0077] Spatulae may also be formed by lithographically induced self construction. With this technique, electrostatic attraction is used to pull liquid through a mask, and thereby "sprout" spatulae. This process is shown in connection with FIG. 10A-10D.

[0078] FIG. 10A illustrates a growing layer 170 positioned on a substrate 172. The growing layer may be molten polymer or thermoplastic. Spacers 174 are positioned on the substrate 172



and a mask 176 is constructed on the spacers 174. The growing layer 170 is electrostatically attracted to the upper mask layer 176, producing a set of protrusions 178, as shown in FIG. 10C. The resultant spatulae array is shown in FIG. 10D.

[0079] Stalks and spatulae may also be formed from a mold using a nano-imprinting roller. This technique is shown in connection with FIG. 11A-11B. While nano-imprinting techniques of the type shown in FIG. 11A-11B have been used in the prior art, they have not been used to produce spatulae structures.

[0080] FIG. 12 illustrates that a 2-layer photoresists can be formed with different resist exposure sensitivities, so that the upper layer forms, for example, 100 nm square plates that are supported by much longer and thinner pedestals. Standing-wave interference patterns can be used to expose and pattern features to fabricate large area arrays. Similar structures can be made with SiO<sub>x</sub> layers on silicon substrates by plasma etching.

[0081] Setae shafts may be fabricated using a sandwich of polymer layers. A polymer layer can include spin-cast polymer materials, such as photoresist, polyimide, glass, or epoxy-based compounds. A polymer layer can also include spray-deposited polymer materials, such as photoresist, polyimide, glass, or epoxy-based compounds. Alternately, a polymer layer may be an ultra-violet curable epoxy.

[0082] FIG. 13 illustrates a manipulator 200 formed in accordance with an embodiment of the invention. The manipulator 200 includes a beam 202 with a set of setae 26A-26D arranged in opposing pairs (e.g., 26A and 26C oppose one another, as do 26B and 26D). The beam 202 is pushed toward the substrate 204 to preload and spread the setae 26A-26D. The beam 202 is then pulled away from the substrate 204 to drag and pick-up the substrate 204. The beam 202 is pushed toward the substrate 204 to release the setae 26A-26D.

[0083] Those skilled in the art will recognize that the adhesive microstructures of the invention may be utilized in a variety of ways. For example, the technique of the invention can be used in pick and place micromanufacturing, micromanipulation, and microsurgery applications. For example, a seta can be attached to a micromanipulator to pick up a fiber optic, move it, and put it down again. Other uses include manipulating retinal prosthesis

implants/explants, attaching to nerves during surgery, and pick and place of silicon wafers or disk drive components.

**[0084]** The setae of the invention may also be used as clutch mechanisms in micromachines. Since setae adhere in a directional manner, a seta could be used as a clutch mechanism similar to a ratchet, but on a smooth surface.

**[0085]** Other applications for the technique of the invention include: insect trapping, tape, robot feet or treads, gloves/pads for climbing, gripping, etc., clean room processing tools, micro-optical manipulation that does not scar a surface and leaves no residue or scratches, micro-brooms, micro-vacuums, flake removal from wafers, optical location and removal of individual particles, climbing, throwing, and sticker toys, press-on fingernails, silent fasteners, a substrate to prevent adhesion on specific locations, a broom to clean disk drives, post-it notes, band aids, semiconductor transport, clothes fasteners, and the like. In many of these applications, patches of spatula on a planar substrate are used, as opposed to patches of spatula positioned on a shaft.

**[0086]** With reference to FIG. 14, a fabricated micron-scale structure 1402 is depicted with a plurality of nano-structures 1404 attached to a base 1406. In one exemplary embodiment, nano-structures 1404 are seta structures, and base 1406 is a substrate, which can be rigid or flexible. Thus, in this exemplary embodiment, FIG. 14 depicts seta structures, disposed on a substrate, adhering to contact surface 1408 using intermolecular forces, and, in particular, van der Waals forces.

**[0087]** As described above, a seta structure has a shaft with an end that adheres to contact surface 1408. As also described above, the end of the shaft that adheres to contact surface 1408 can have essentially the same shape as the shaft, or can have one or more spatula structures, which may be in the form of a paddle or flattened surface, a flattened segment of a sphere, an end of a cylinder, a sphere, a blunt end, a bent cylinder, or any suitable shape.

**[0088]** In another exemplary embodiment, nano-structures 1404 are spatula structures, and base 1406 is a seta structure. Thus, in this exemplary embodiment, FIG. 14 depicts spatula structures, disposed on a seta structure, adhering to contact surface 1408 using intermolecular forces, and, in particular, van der Waals forces.

[0089] As described above, with reference to FIG. 11, a single seta of a Tokay gecko is depicted engaged with an aluminum wire used as a force gauge. With reference to FIG. 15, results of an experiment are depicted where the force of detachment was measured for various angles of detachment of the seta. As depicted in FIG. 15, contact was broken when the seta was pulled at an angle greater than 30 degrees relative to the contact surface. (See, K. Autumn, Y. Liang, T. Hsieh, W. Zesch, W.-P. Chan, T. Kenny, R. Fearing, and R.J. Full, adhesive Force of a Single Gecko Foot-Hair”, Nature, vol. 405, pp. 681-685 (June 8, 2000).)

[0090] 1. Nano-structure Design for Minimum Peel Strength

[0091] With reference to FIG. 16, in one exemplary embodiment, base 1406 includes nano-structures 1404 attached at one portion of base 1406. It should be recognized that nano-structures 1404 can be a single structure or a plurality of structures, such as plates or spheres. In the present exemplary embodiment, when nano-structures 1404 adhere to contact surface 1408 and an external force is applied to peel base 1406 from contact surface 1408, nano-structures 1404 are disposed on a portion of base 1406 located at a distance away from where the external force acts such that the distance defines a moment arm for the applied external force to peel base 1406 from contact surface 1408.

[0092] In particular, assume that base 1406 can be modeled as a rigid beam, and neglect geometry changes due to bending. While a compliant base 1406 would slightly change the magnitudes, the overall results would be similar. As depicted in FIG. 16, a portion  $l$  of the overall length of base 1406 includes nano-structures 1404, while a portion  $s$  does not include nano-structures 1404. Thus, the overall length of base 1406 is  $(l+s)$ . Assume that all of nano-structures 1404 are in contact with contact surface 1408 with a uniform adhesive pressure of  $P_oNm^{-1}$ . As depicted in FIG. 16, height  $h$  corresponds to the height of nano-structures 1404. Assume a Coulomb friction model with coefficient of friction  $\mu$ , and  $F_f = \mu F_n$ .

[0093] Now assume a force  $T$  acts at angle  $\theta$  to pull base 1406 off contact surface 1408. There are three possible conditions: sliding, lifting, and pivoting.

[0094] Sliding is characterized by equation (1):

$$T\cos\theta > \mu(P_o l - T\sin\theta). \quad (1)$$

[0095] Lifting is characterized by equation (2):

$$T \sin \theta > P_o l. \quad (2)$$

[0096] Pivoting is characterized by equation (3):

$$T(s+l) \sin \theta > T h \cos \theta + \int_0^l P_o x dx, \quad (3)$$

or, for a particular angle  $\theta$ :

$$T > \frac{P_o l^2}{2} \frac{1}{(s+l) \sin \theta - h \cos \theta}. \quad (4)$$

[0097] As depicted in FIG. 17, for pull angles of less than approximately  $30^\circ$ , the nano-structure slides on the contact surface. FIG. 17 depicts the maximum pure tensile force  $T$  (in  $\mu\text{N}$ ) before sliding or peeling, with  $P_o=800\mu\text{N}$ ,  $l=200\mu\text{m}$ ,  $s=110\mu\text{m}$ ,  $\mu=0.25$ , and  $h=20\mu\text{m}$ . As depicted in FIG. 17, for angles greater than  $30^\circ$ , the nano-structure peels off, with the force required for peeling dropping dramatically at higher pulling angles. The nano-structure can stand three times more load in shear than in the normal direction.

[0098] With reference again to FIG. 16, as described above, in one exemplary embodiment, nano-structures 1404 are seta structures, and base 1406 is a substrate. Thus, in this exemplary embodiment, FIG. 16 depicts seta structures disposed on one portion of a substrate.

[0099] As also described above, the end of a seta structure that adheres to contact surface 1408 can have essentially the same shape as the shaft of the seta structure, or can have one or more spatula structures. If the end of the seta structure has multiple spatula structures, the spatula structures can be oriented in the same direction or in opposing directions.

[00100] In another exemplary embodiment, nano-structures 1404 are spatula structures, and base 1406 is a seta structure. Thus, in this exemplary embodiment, FIG. 16 depicts spatula structures disposed on one portion of a seta structure.

**[00101]** 2. Nano-structure Design for Maximum Peel Strength

**[00102]** With reference to FIG. 18, in another exemplary embodiment, base 1406 includes at least one nano-structure 1404 attached at opposing locations on base 1406. Thus, in the present exemplary embodiment, when nano-structures 1404 adhere to contact surface 1408 and an external force is applied to peel base 1406 from contact surface 1408, nano-structures 1404 located at opposing locations on base 1406 resist torque resulting from the applied external force.

**[00103]** In particular, assume a force  $T$  acts at angle  $\theta$  in the middle of base 1406 to pull base 1406 away from contact surface 1408. Again, there are three possible conditions: sliding, lifting, and pivoting.

**[00104]** The sliding force  $T$  is the same as in equation (1), and the lift off force  $T$  is the same as in equation (2). Pivoting, however, can be characterized by equation (5):

$$T(s+l)\sin\theta > Th\cos\theta + \int_0^{l/2} P_0 x dx + \int_{s+l/2}^{s+l} P_0 x dx, \quad (5)$$

or, for a particular angle  $\theta$ :

$$T > \frac{P_0 l(s+l)}{2} \frac{1}{\frac{s+l}{2} \sin\theta - h \cos\theta}. \quad (6)$$

**[00105]** As depicted in FIG. 19, as compared to FIG. 17, the shear strength remains the same ( $200\mu\text{N}$ ) at  $\theta=0^\circ$ , but the nano-structure slide rather than peel. As compared to FIG. 17, pulloff force at  $\theta=90^\circ$  is an order of magnitude higher for the same adhesive force at the nano-structure and the same dimensions.

**[00106]** Thus, with reference to FIGs. 16 and 18, one or more nano-structures 1404 can be located on portions of base 1406 to facilitate or inhibit peeling of base 1406 from contact surface 1408. In particular, with reference to FIG. 16, to facilitate peeling, one or more nano-structures 1404 are disposed on base 1406 in a location to produce torque from an applied external force. With reference to FIG. 18, to inhibit peeling, nano-structures 1404 are disposed on base 1406 in opposing locations to resist torque from an applied external force.

[00107] In other exemplary embodiments, various geometric shapes and patterns of nano-structures can be used. For example, radially oriented nano-structures can provide resistance to peel off in all directions. In addition, suction-cup like structures covered with nano-structures can be used to engage the nano-structures in a radial direction. Such a suction cup-like structure would not rely on vacuum for adhesion, and thus such a device would stick underwater or in vacuum.

[00108] With reference again to FIG. 18, as described above, in one exemplary embodiment, nano-structures 1404 are seta structures, and base 1406 is a substrate. Thus, in this exemplary embodiment, FIG. 18 depicts seta structures disposed on opposing locations on a substrate to resist torque from an applied external force. For example, as described above, FIG. 13 depicts a set of setae 26A-26D (seta structures) arranged in opposing pairs on beam 202 (substrate).

[00109] With reference again to FIG. 18, as also described above, the end of a seta structure that adheres to contact surface 1408 can have essentially the same shape as the shaft of the seta structure, or can have one or more spatula structures. If the end of the seta structure has multiple spatula structures, the spatula structures can be oriented in the same direction or in opposing directions.

[00110] In another exemplary embodiment, nano-structures 1404 are spatula structures, and base 1406 is a seta structure. Thus, in this exemplary embodiment, FIG. 18 depicts spatula structures disposed on opposing locations on a seta structure to resist torque from an applied external force.

[00111] The foregoing description, for purposes of explanation, used specific nomenclature to provide a thorough understanding of the invention. However, it will be apparent to one skilled in the art that the specific details are not required in order to practice the invention. Thus, the foregoing descriptions of specific embodiments of the present invention are presented for purposes of illustration and description. They are not intended to be exhaustive or to limit the invention to the precise forms disclosed, obviously many modifications and variations are possible in view of the above teachings. The embodiments were chosen and described in order to best explain the principles of the invention and its practical applications, to thereby enable others skilled in the art to best utilize the invention and various embodiments with various modifications as are suited to the particular use contemplated. It is intended that the scope of the invention be defined by the following claims and their equivalents.

We claim:

1. A fabricated microstructure, comprising:  
a base; and  
one or more nano-structures disposed on one or more portions of the base to adhere to a contact surface,  
wherein the one or more portions having the one or more nano-structures are located on the base such that, when the one or more nano-structures adhere to the contact surface and an external force is applied to peel the base from the contact surface, the one or more nano-structures in the one or more portions of the base facilitate or resist peeling of the nano-structures from the contact surface.
2. The fabricated microstructure of claim 1, wherein one portion having the one or more nano-structures is located a distance away from a portion of the base where the external force acts to peel the base from the contact surface, and wherein the distance defines a moment arm for the applied external force to peel the base from the contact surface.
3. The fabricated microstructure of claim 2, wherein the base is a substrate, and wherein the nano-structures are seta structures.
4. The fabricated microstructure of claim 2, wherein the base is a seta structure, and wherein the nano-structures are spatula structures.
5. The fabricated microstructure of claim 4, wherein the spatula structures are oriented in the same direction or opposing directions.
6. The fabricated microstructure of claim 1, wherein at least two portions in opposing locations on the base have one or more nano-structures, wherein the one or more nano-structures in the opposing locations resist torque resulting from the applied external force.
7. The fabricated microstructure of claim 6, wherein the at least two portions are located equal distance in opposite directions from where a normal component of the external force acts to peel the base from the contact surface.



8. The fabricated microstructure of claim 6, wherein the base is a substrate, and wherein the nano-structures are seta structures.
9. The fabricated microstructure of claim 6, wherein the base is a seta structure, and wherein the nano-structures are spatula structures.
10. The fabricated microstructure of claim 9, wherein the spatula structures are oriented in the same direction or opposing directions.
11. The fabricated microstructure of claim 1, wherein each of the at least two portions have a plurality of nano-structures.
12. The fabricated microstructure of claim 1, further comprising:
  - a plurality of nano-structures are disposed on the base in a radial pattern to resist peeling from a contact surface.
13. The fabricated microstructure of claim 12, wherein the base is circular in shape.
14. The fabricated microstructure of claim 1, wherein the one or more nano-structures adhere to the contact surface by intermolecular forces.
15. The fabricated microstructure of claim 14, wherein the intermolecular forces are van der Waals forces.
16. A method of forming a fabricated microstructure to adhere to a contact surface, comprising:
  - forming a base; and
  - forming a plurality of nano-structures disposed on one or more portions of the base to adhere to the contact surface,wherein the one or more portions having the one or more nano-structures are located on the base such that, when the one or more nano-structures adhere to the contact surface and an external force is applied to peel the base from the contact surface, the one or more nano-structures in the one or more portions of the base facilitate or resist peeling of the nano-structures from the contact surface.

17. A method of adhering a fabricated microstructure to a contact surface, comprising:  
obtaining a base having one or more nano-structures disposed on one or more portions of the base; and  
placing the base having the one or more nano-structures on the contact surface,  
wherein the one or more portions having the one or more nano-structures are located on the base such that, when the one or more nano-structures adhere to the contact surface and an external force is applied to peel the base from the contact surface, the one or more nano-structures in the one or more portions of the base facilitate or resist peeling of the nano-structures from the contact surface.
18. A fabricated microstructure, comprising:  
a substrate; and  
at least two seta structures configured to adhere to a contact surface by van der Waals forces, wherein the at least two seta structures are disposed on the substrate in opposing orientation to resist peeling when the at least two seta structures adhere to a contact surface.
19. The fabricated microstructure of claim 18, wherein each seta structure includes one or more spatula structures disposed on one or more portions of each seta structure, and wherein the one or more spatula structures adhere to the contact surface by van der Waals forces.
20. The fabricated microstructure of claim 19, wherein spatula structures disposed on each seta structure are oriented in the same direction or opposing directions.
21. A method of forming a fabricated microstructure, comprising:  
forming a substrate; and  
forming at least two seta structures configured to adhere to a contact surface by van der Waals forces, wherein the at least two seta structures are disposed on the substrate in opposing orientation to resist peeling when the at least two seta structures adhere to a contact surface.
22. A method of adhering a fabricated microstructure to a contact surface, comprising:

obtaining a substrate having at least two seta structures configured to adhere to the contact surface by van der Waals forces; and

placing the substrate having the at least two seta structures on the contact surface,

wherein the at least two seta structures are disposed on the substrate in opposing orientation to resist peeling when the at least two seta structures adhere to a contact surface.

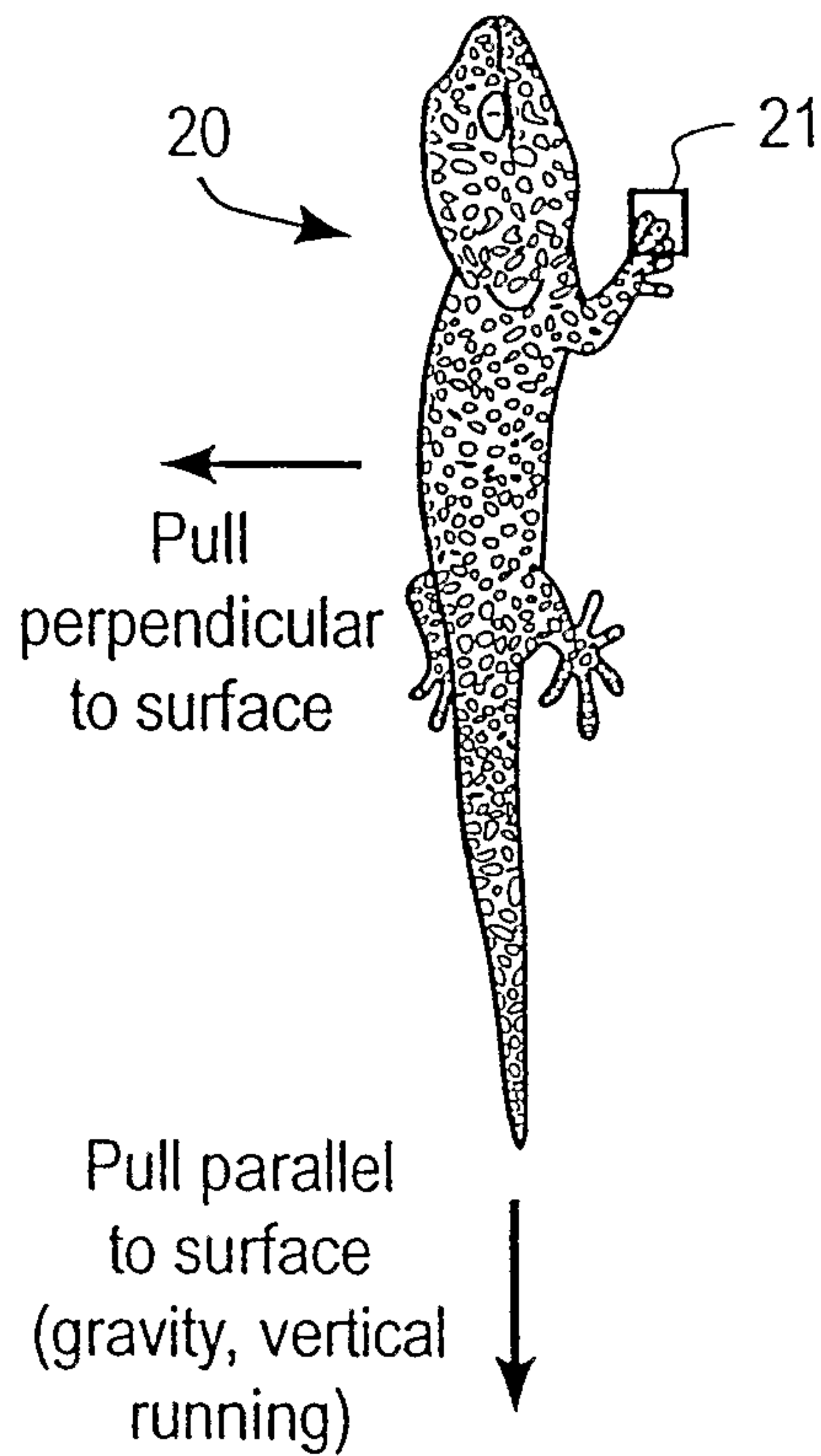


FIG. 1A

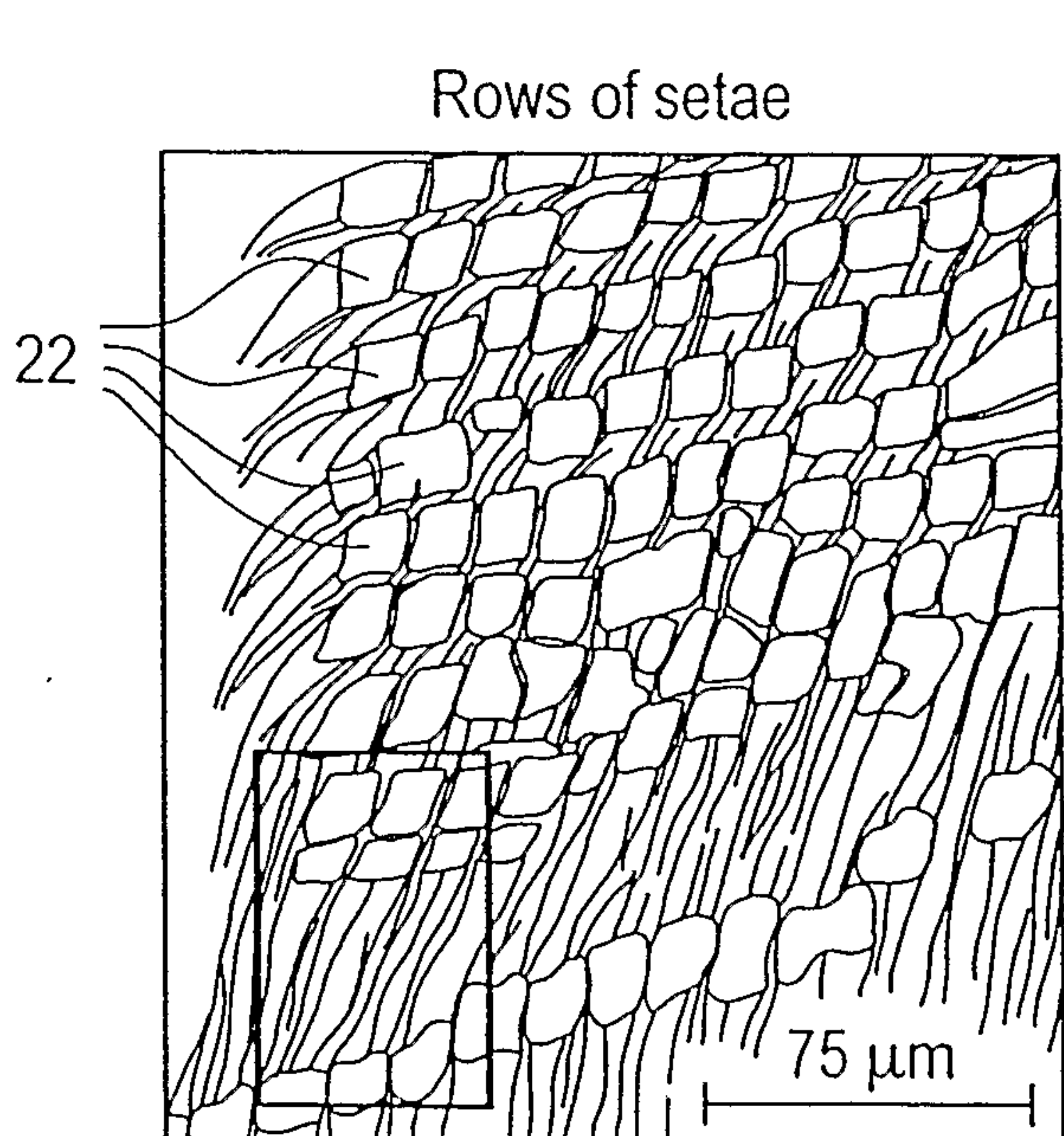


FIG. 1B

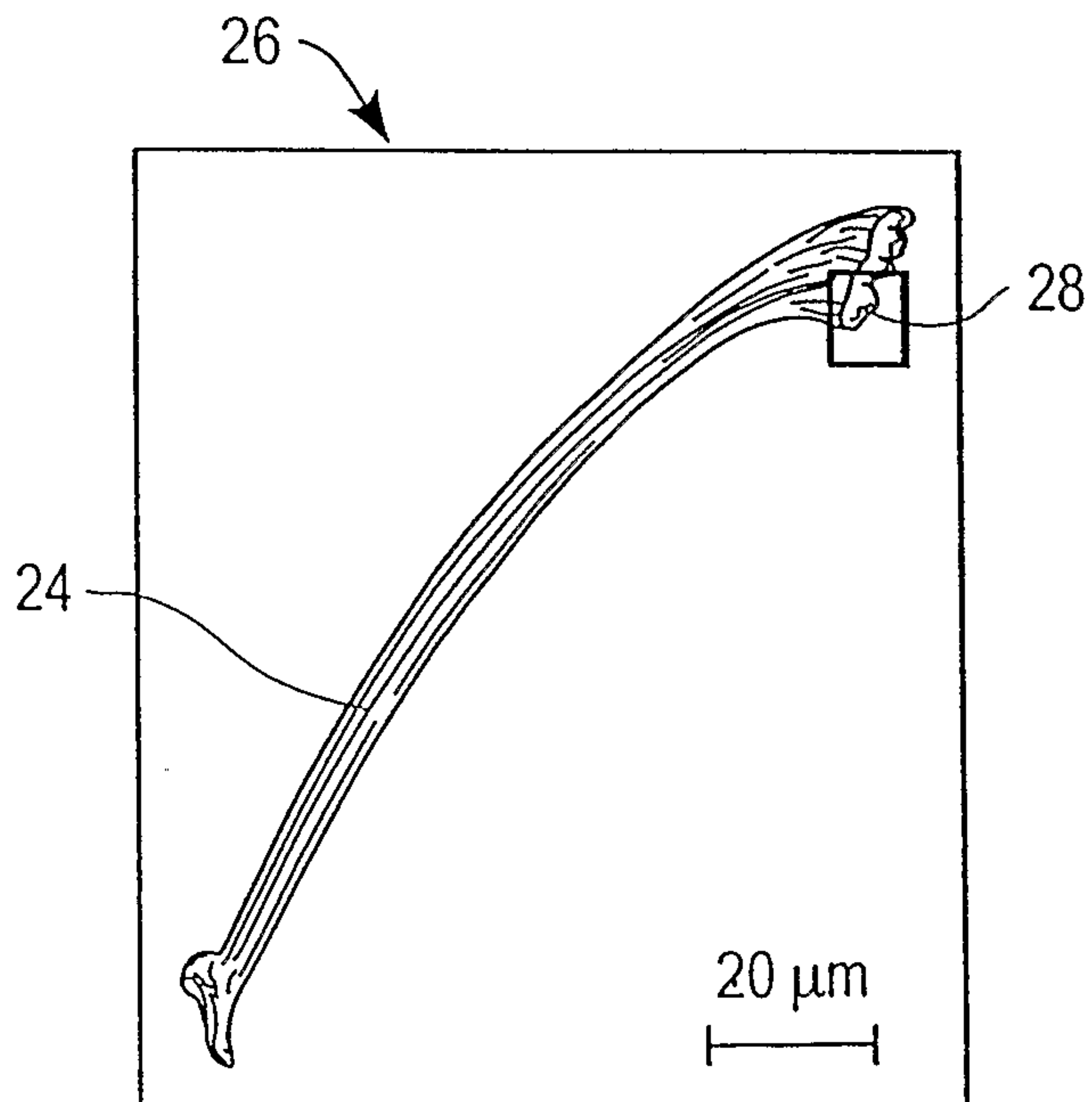


FIG. 1C

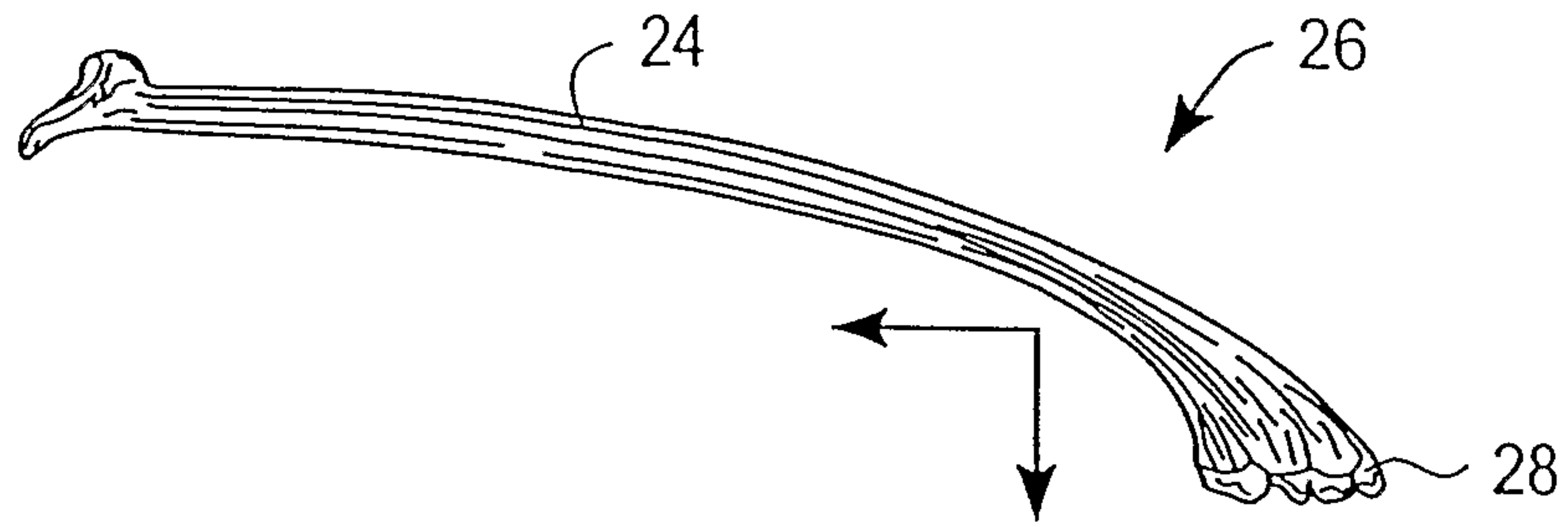


FIG. 1D

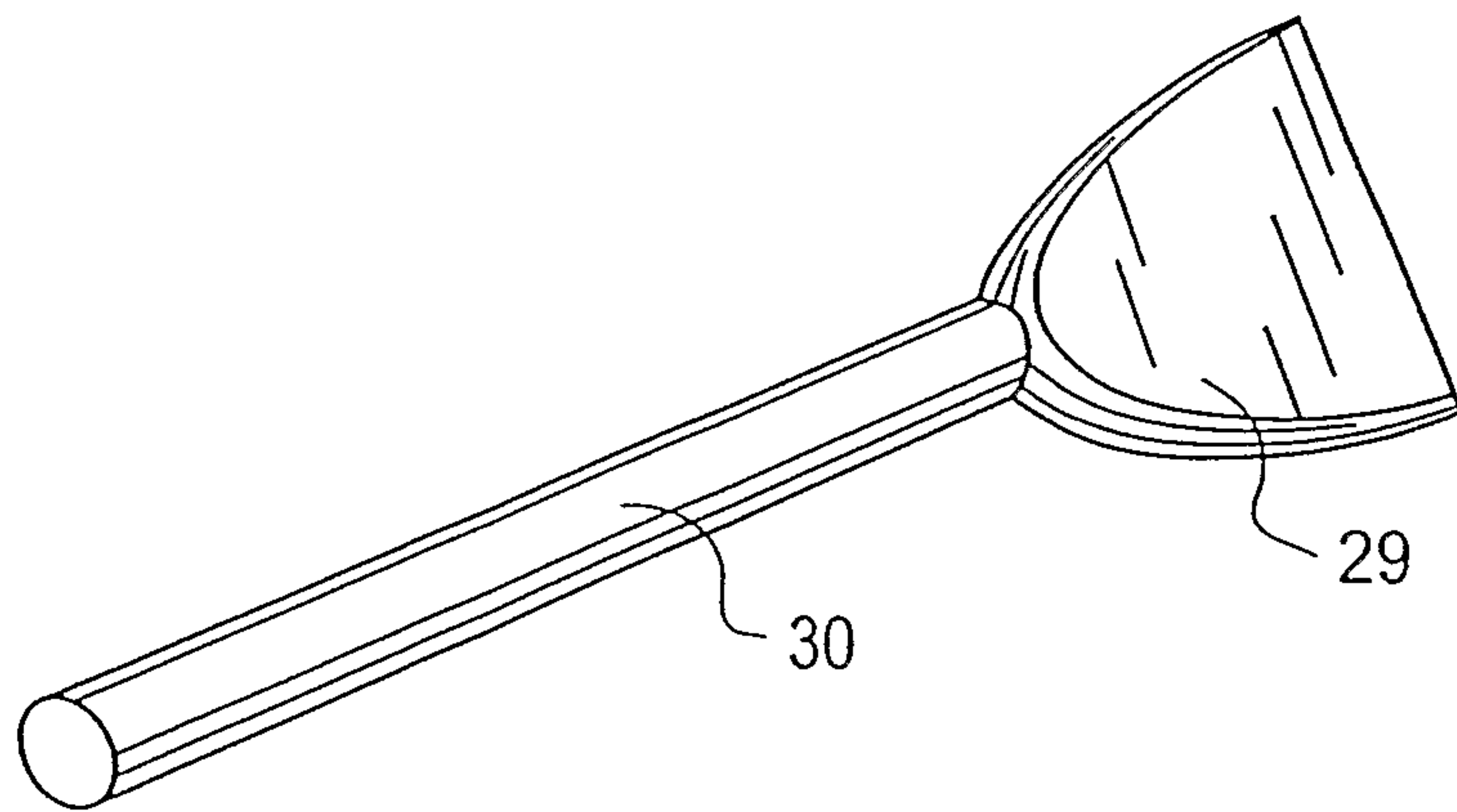


FIG. 1E

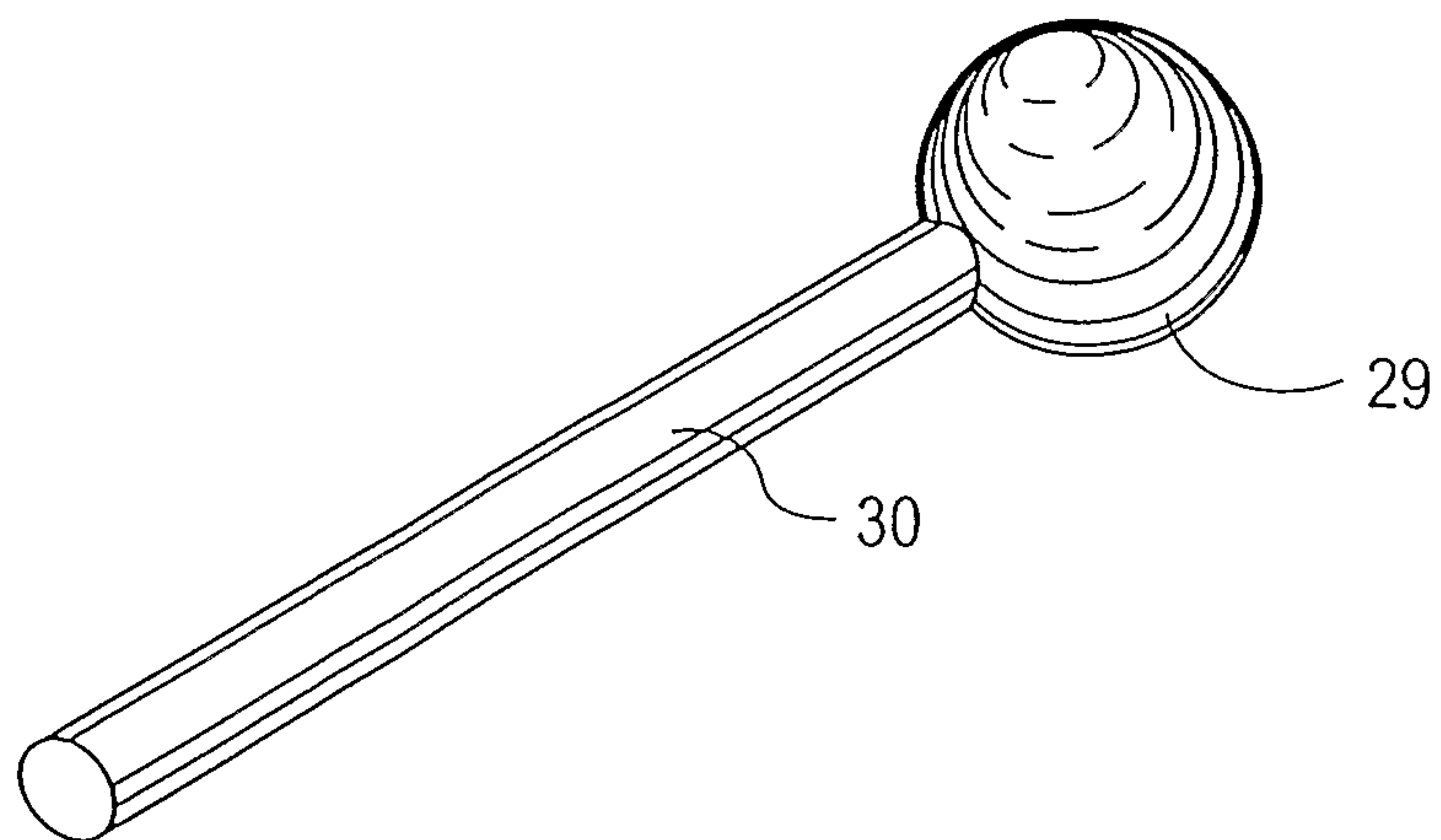


FIG. 1F

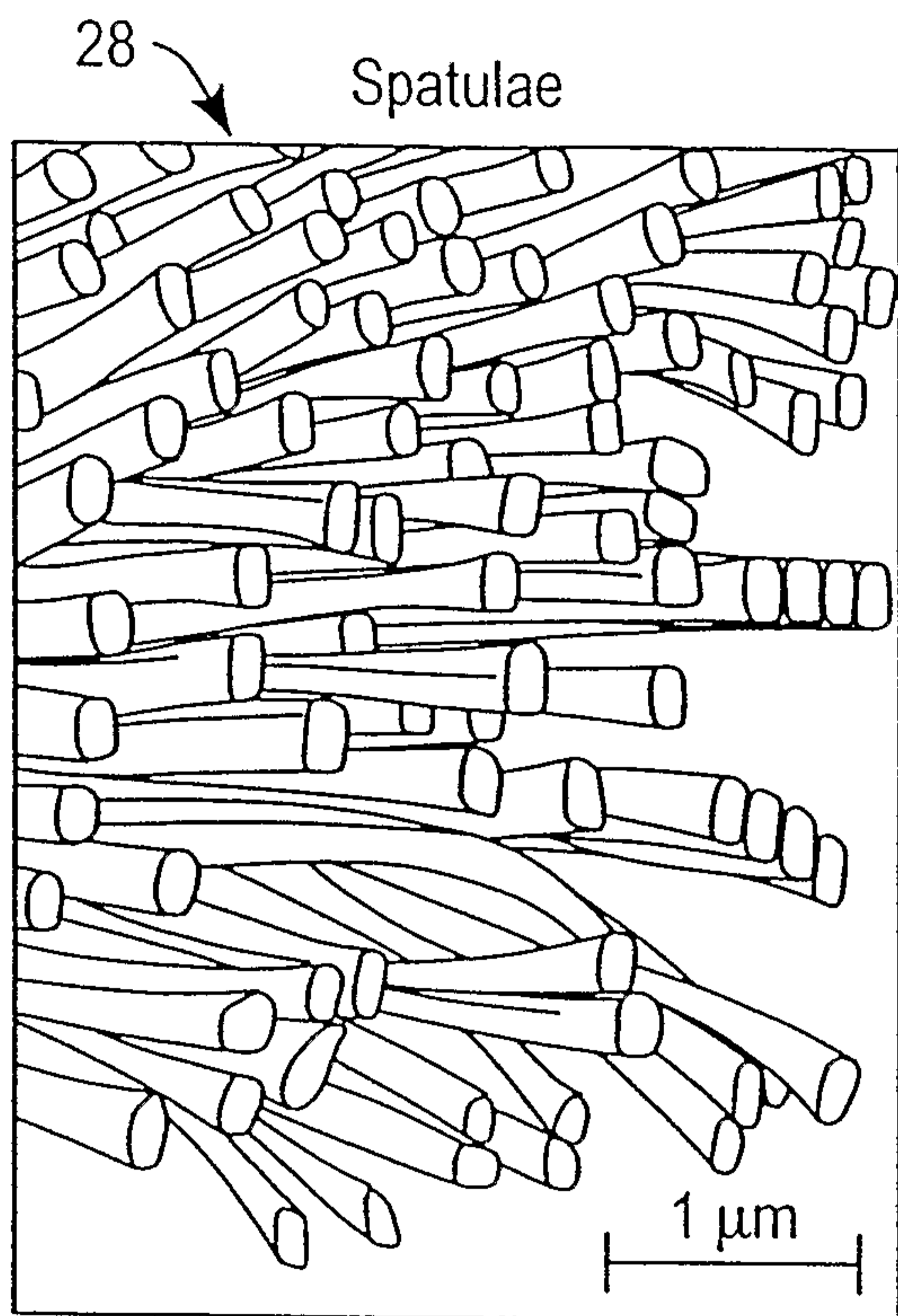


FIG. 1G

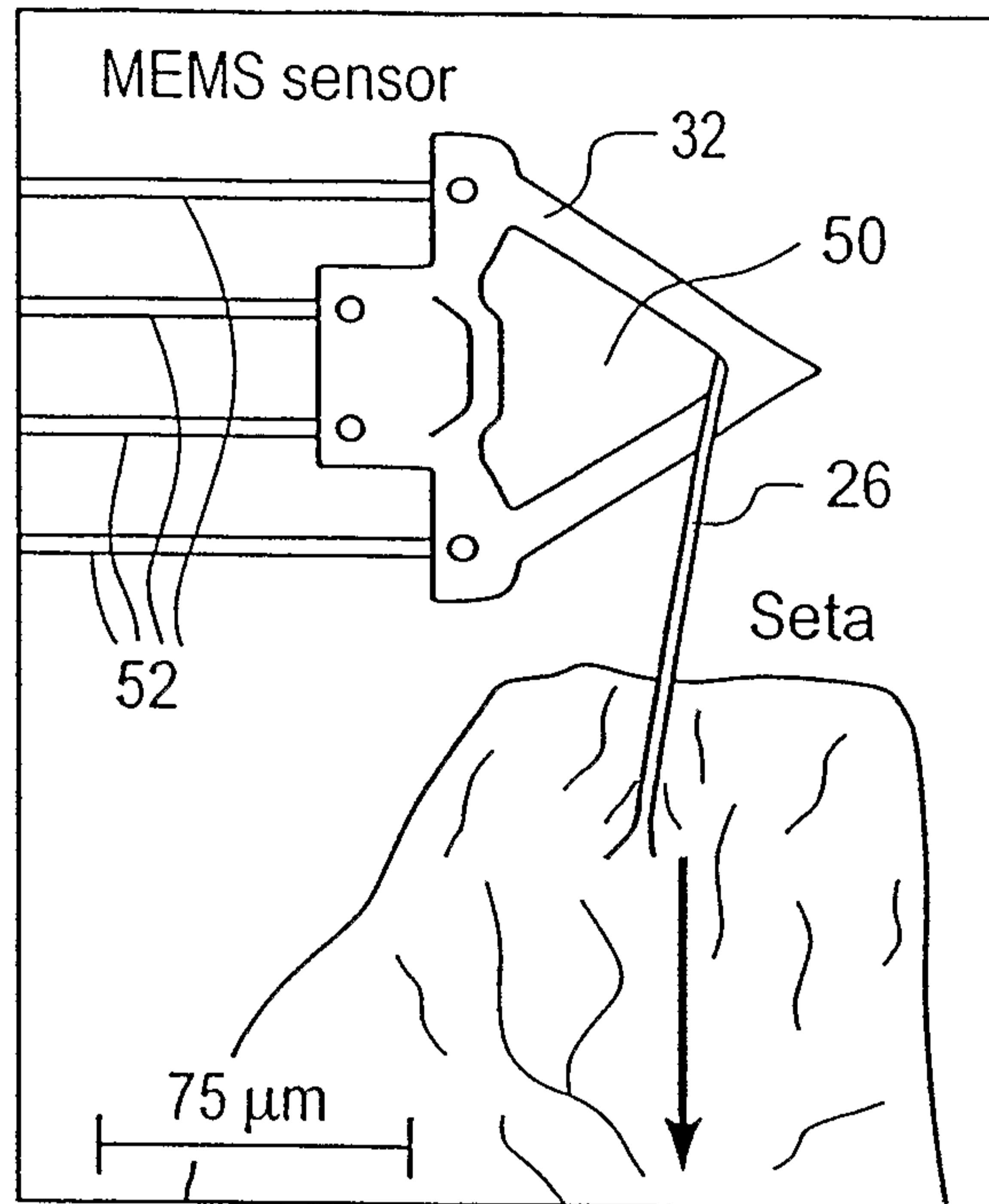


FIG. 1H

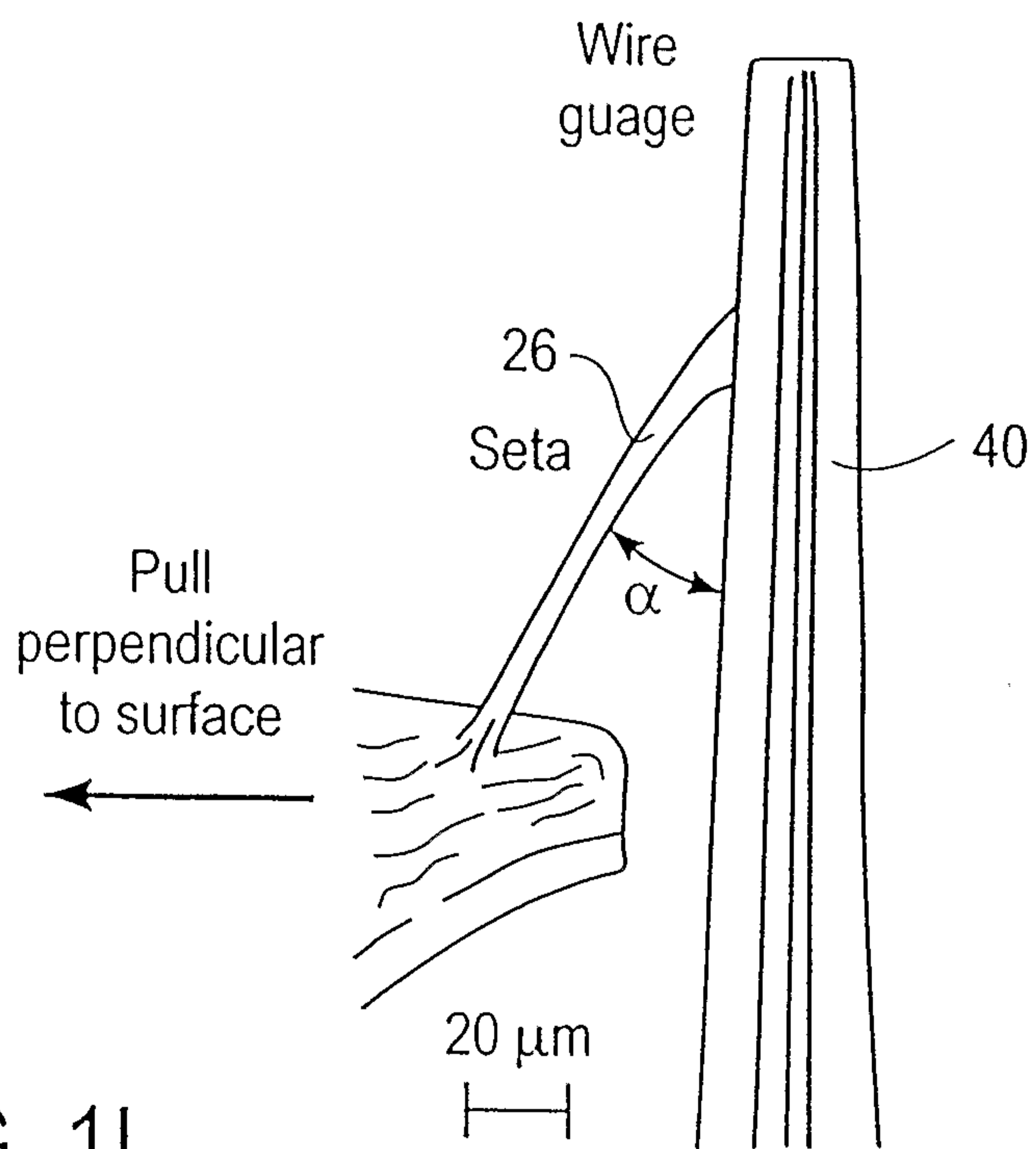


FIG. 1I

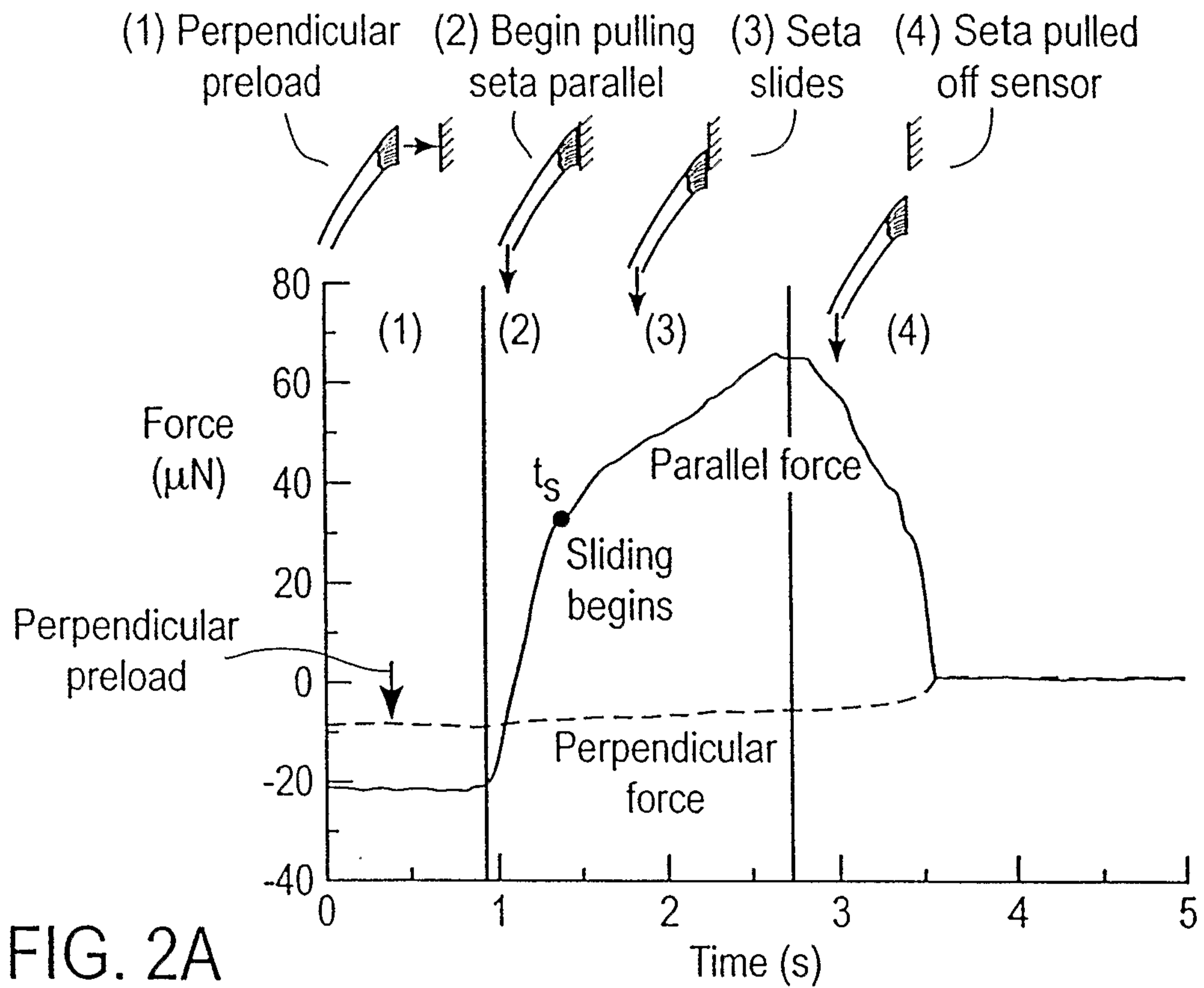


FIG. 2A

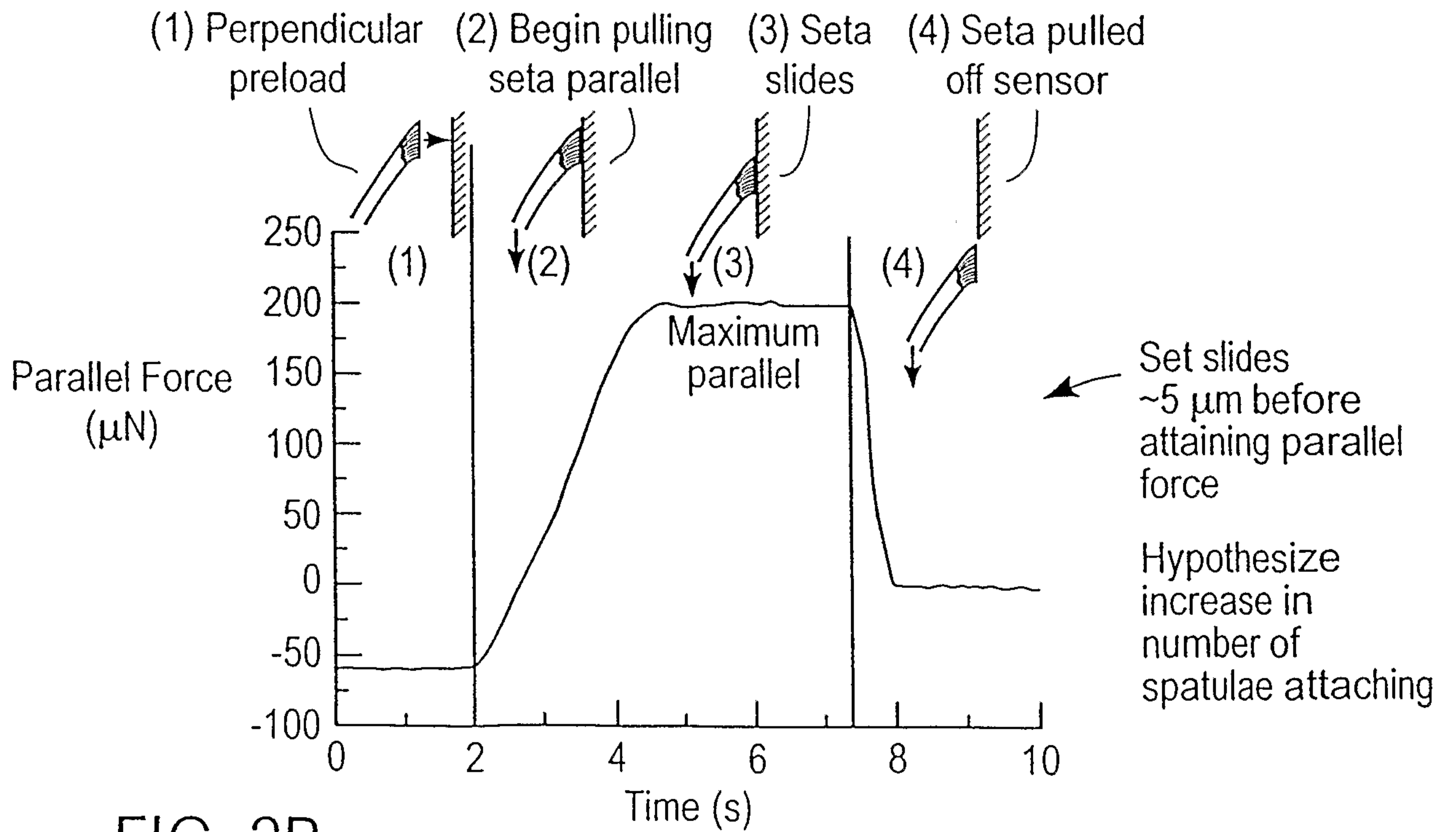


FIG. 2B

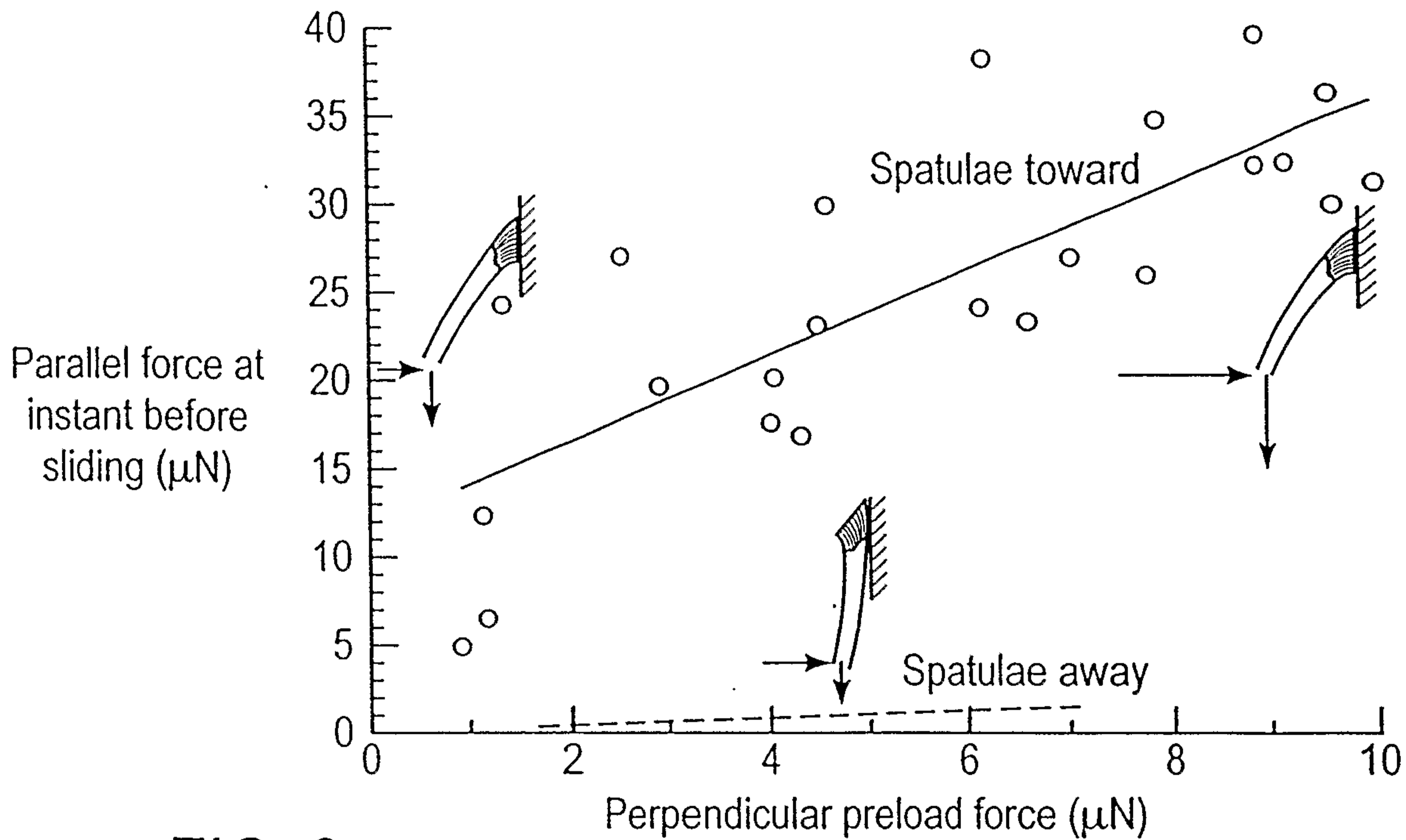


FIG. 3

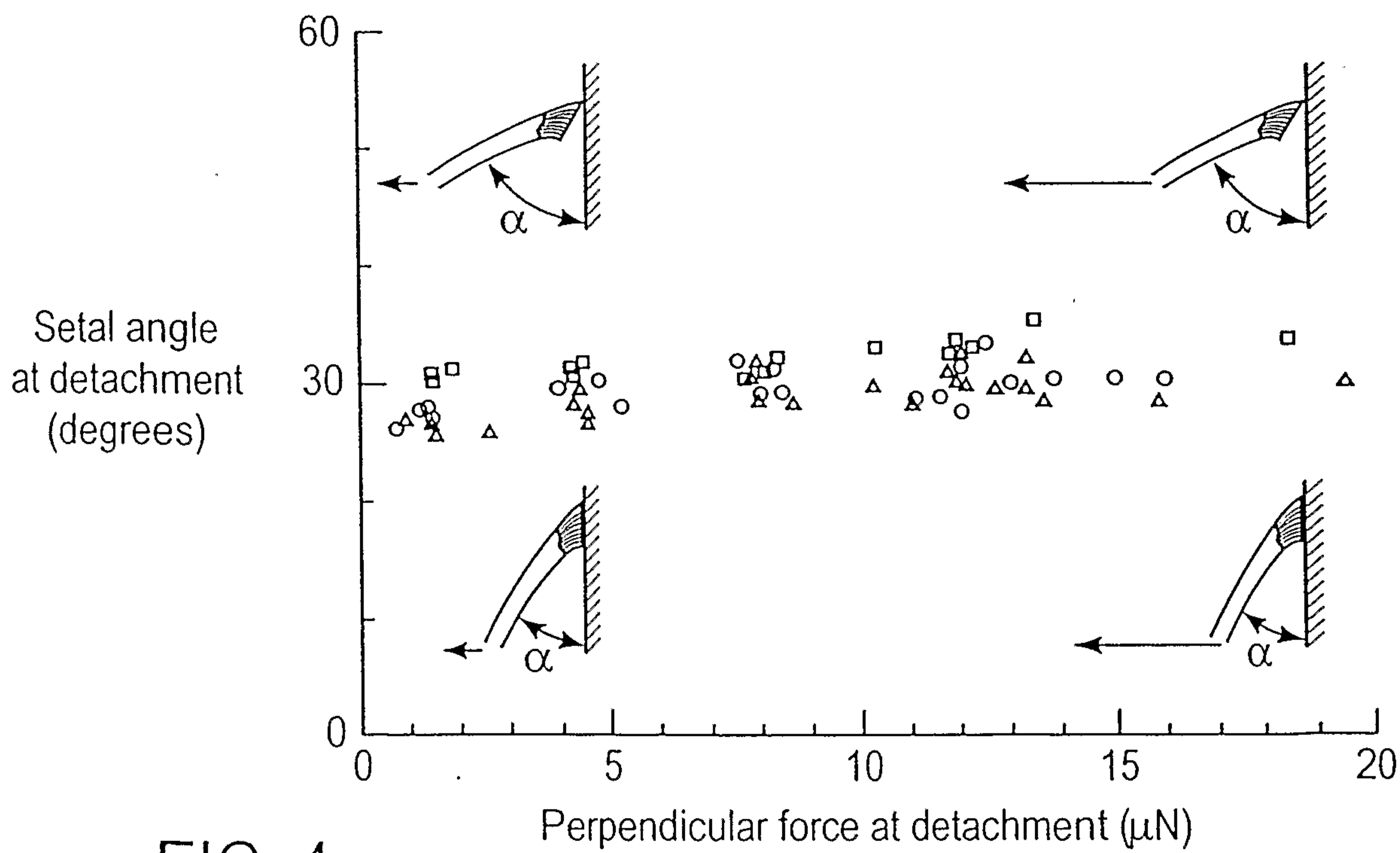


FIG. 4



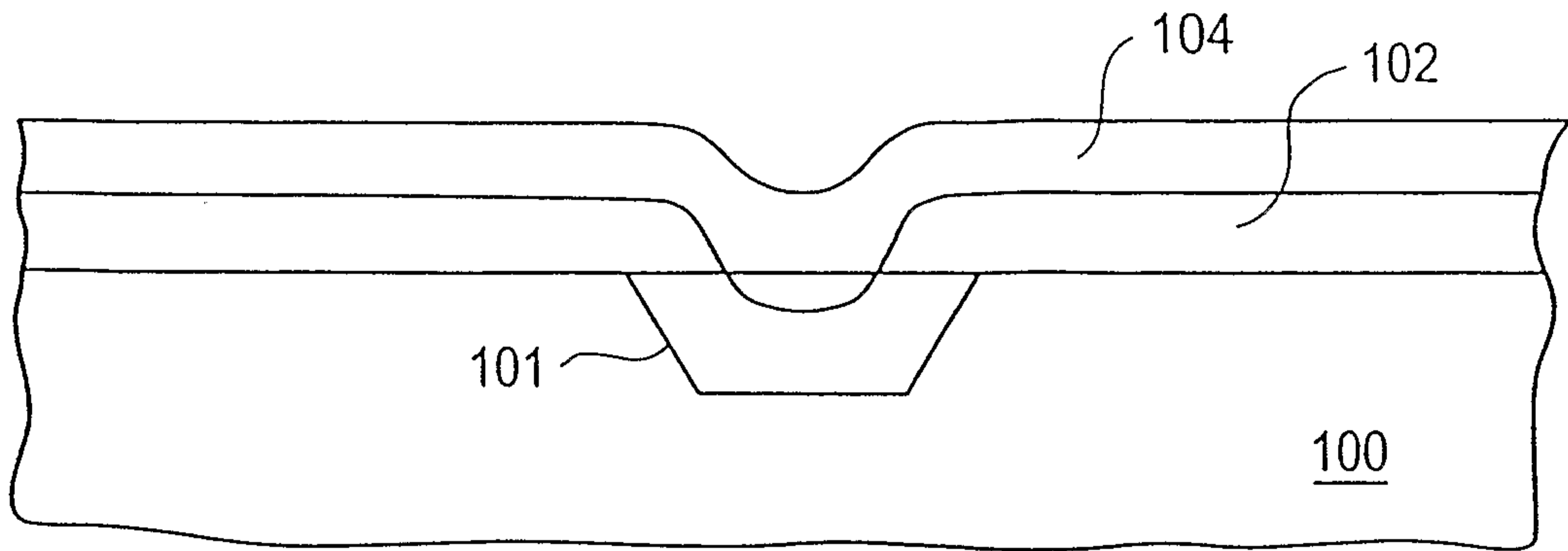


FIG. 5A

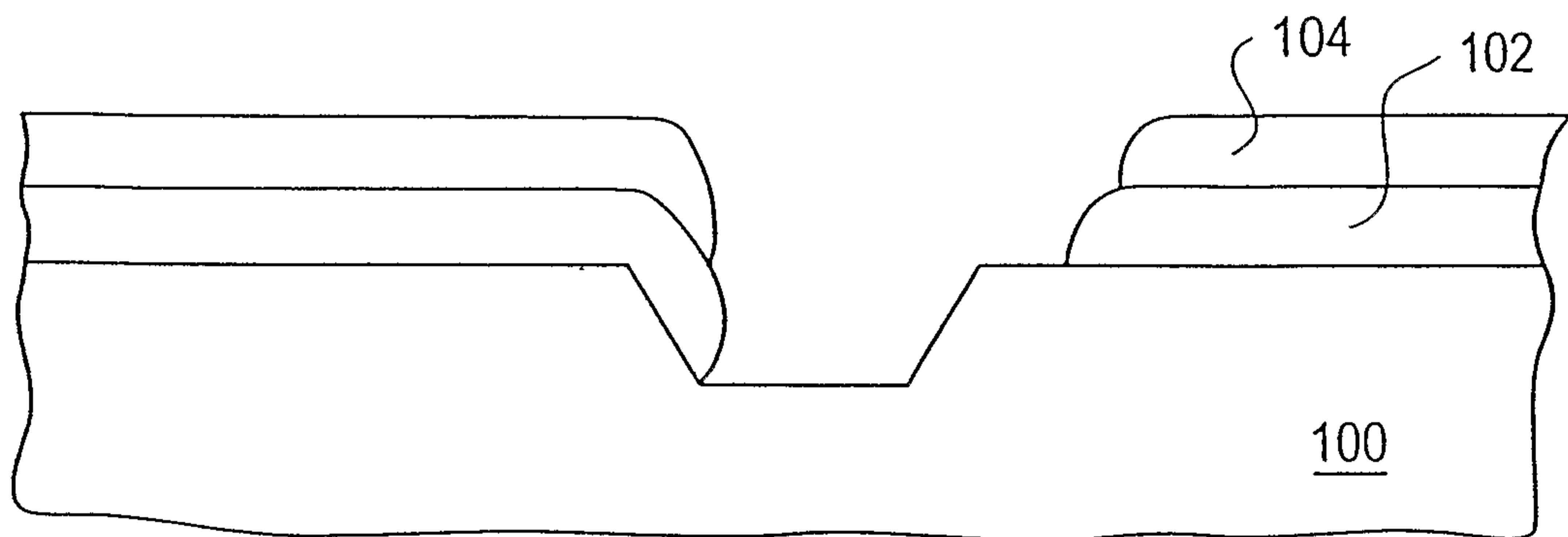


FIG. 5B

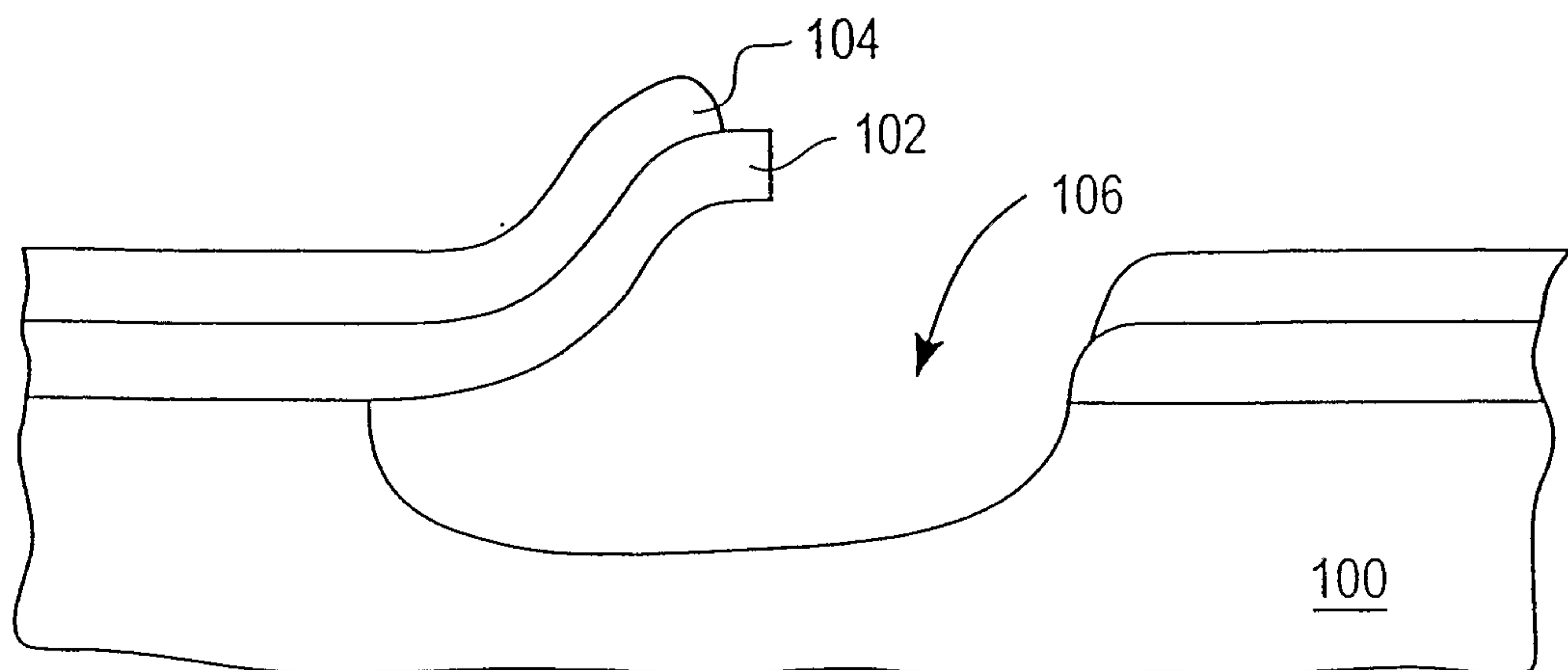


FIG. 5C

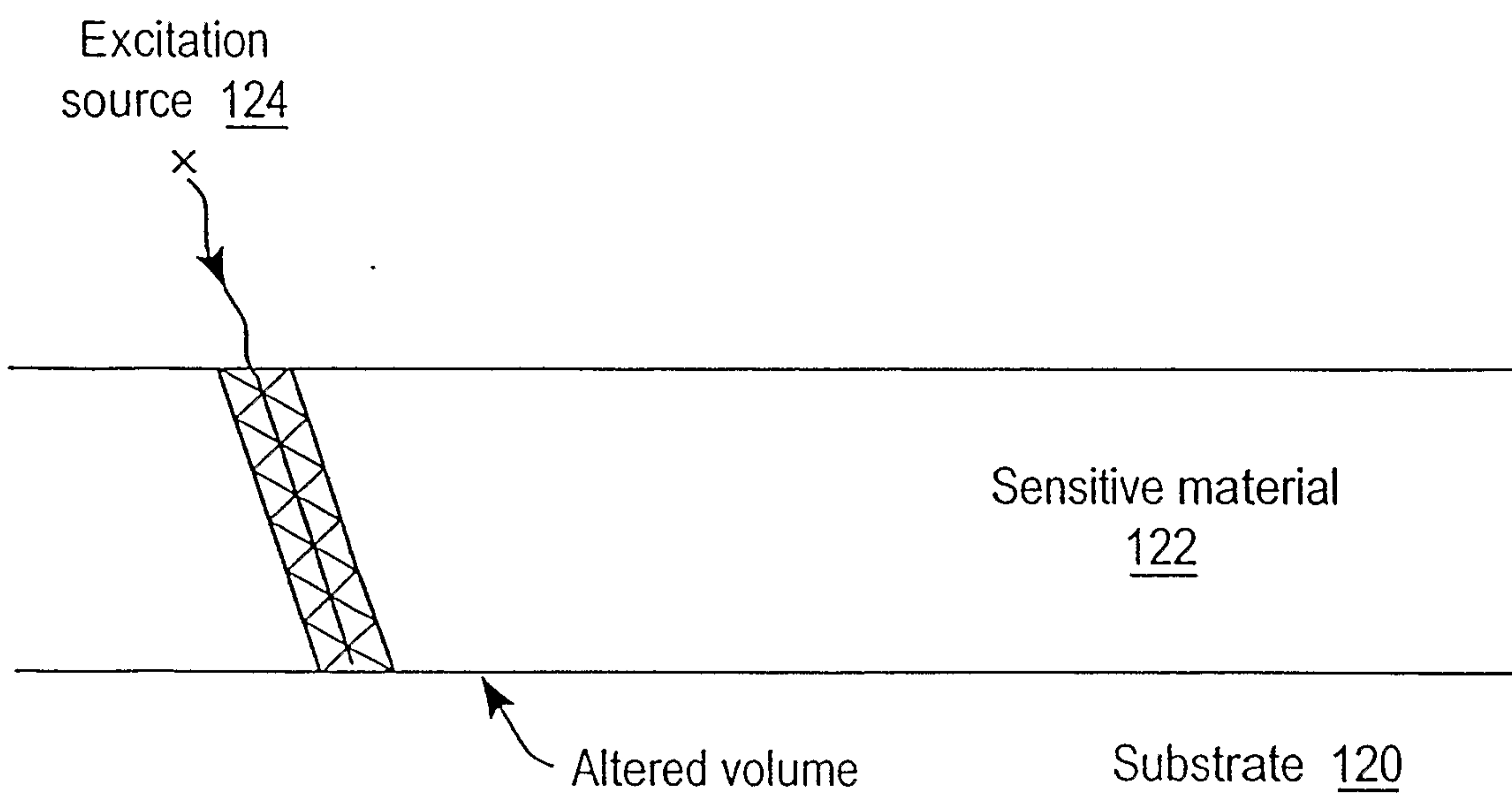


FIG. 6A

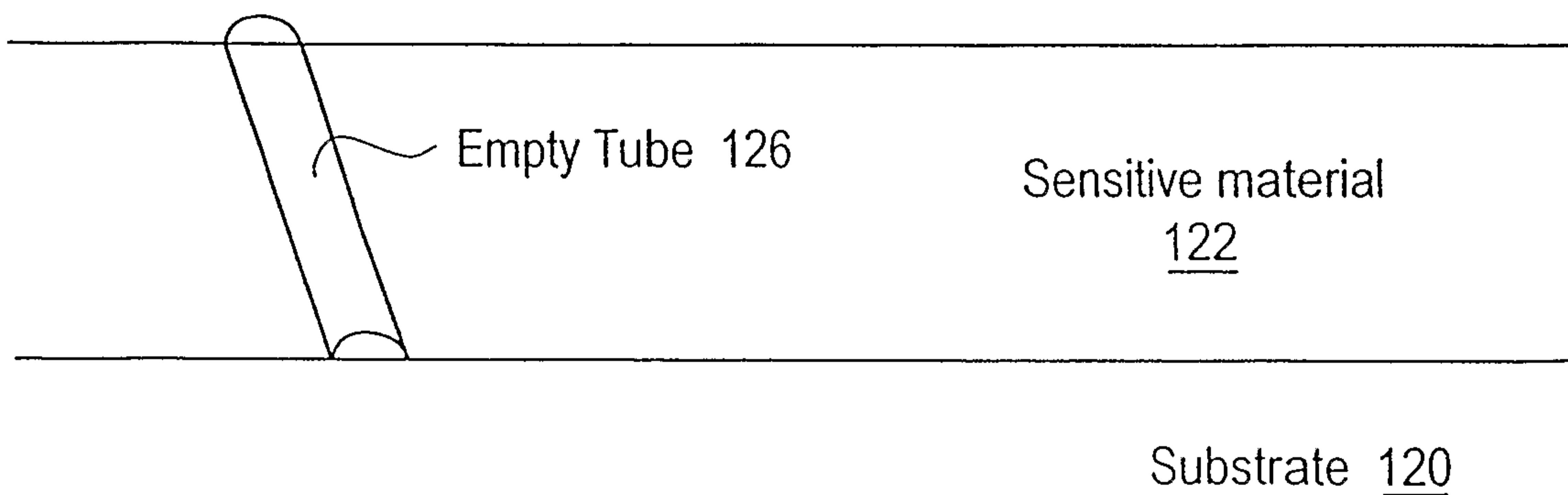


FIG. 6B

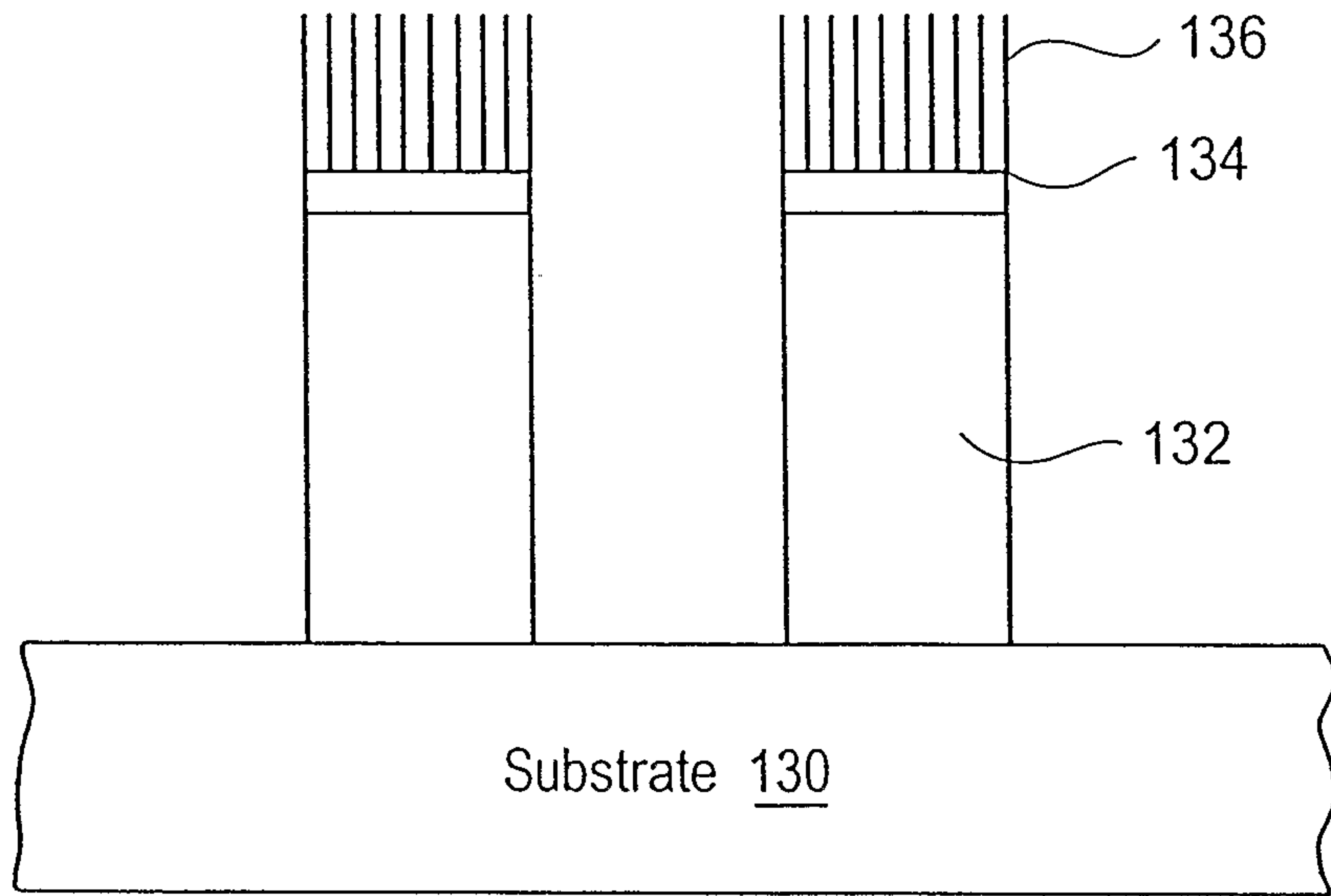


FIG. 7

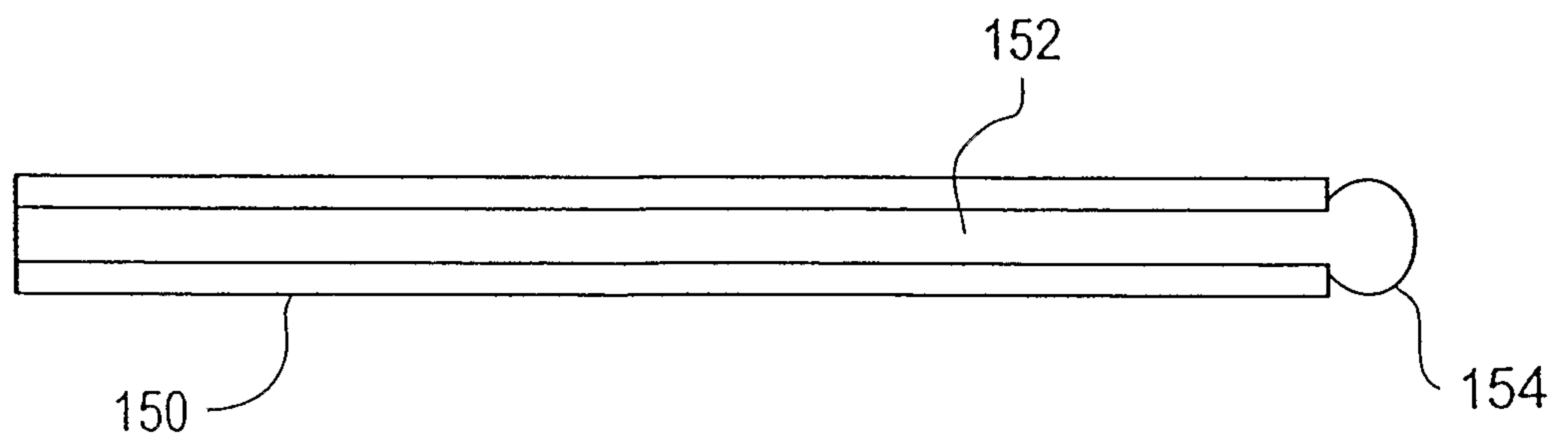


FIG. 8

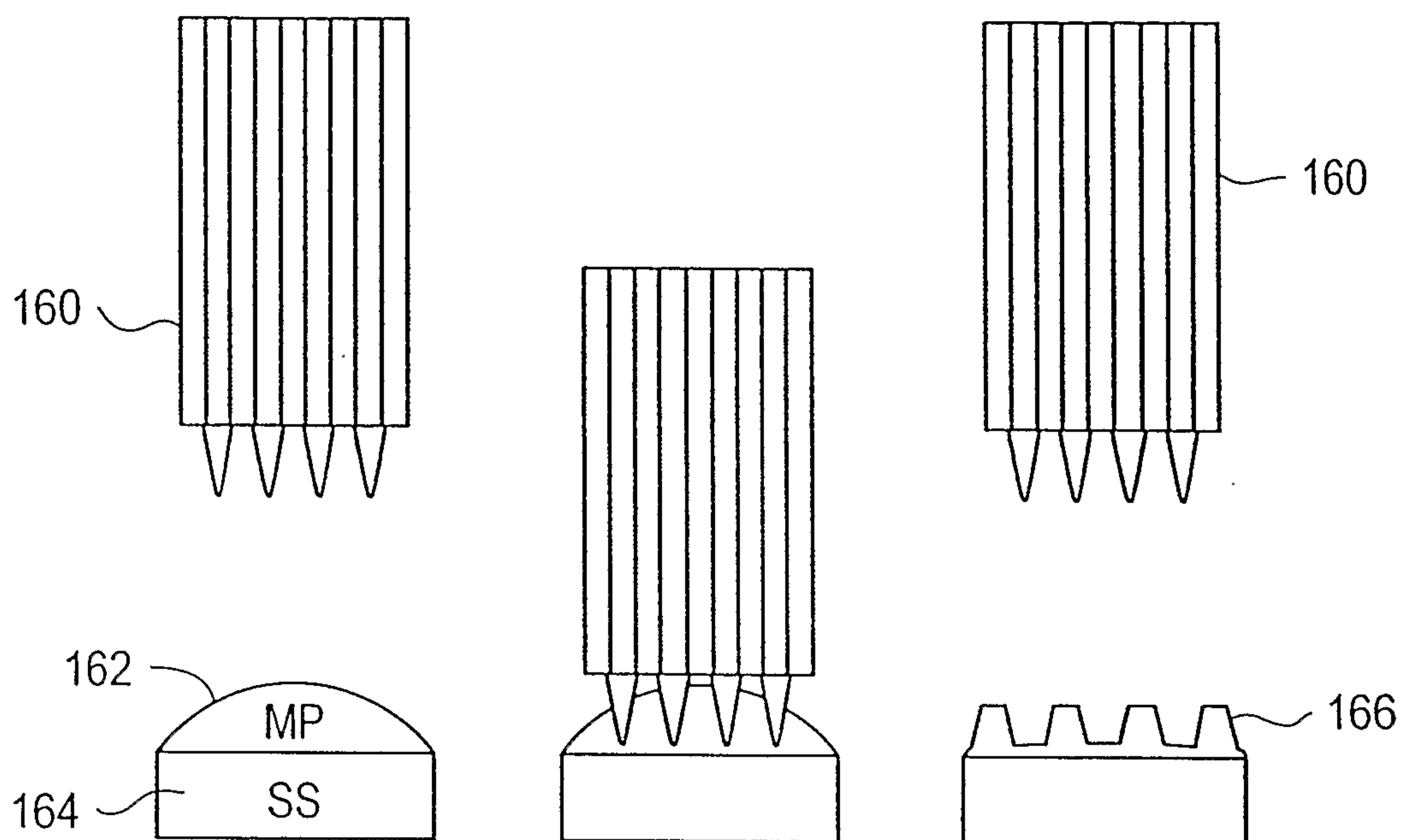


FIG. 9

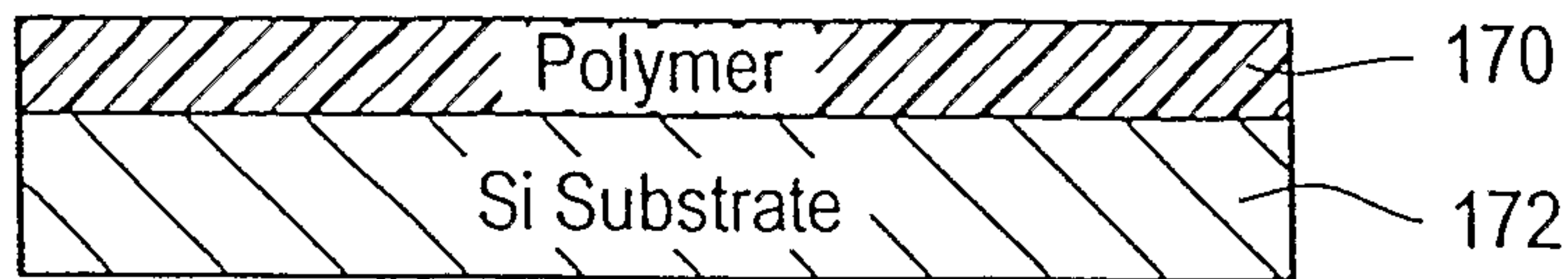


FIG. 10A

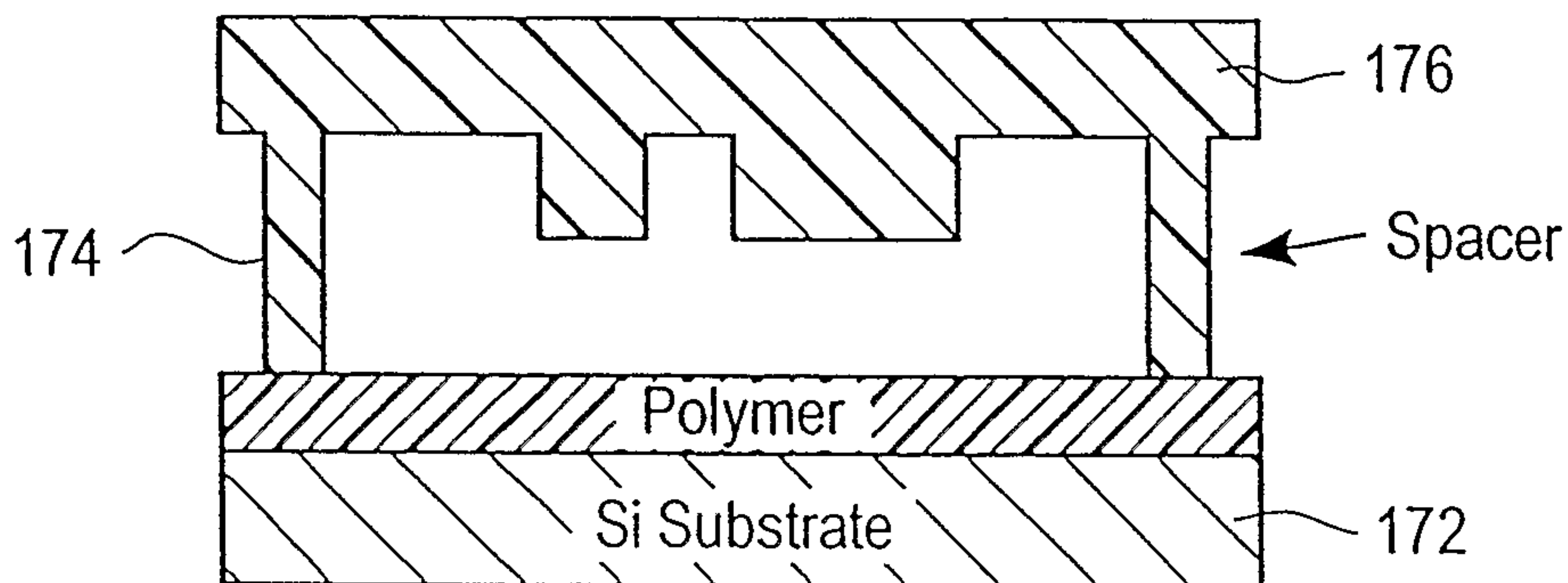


FIG. 10B

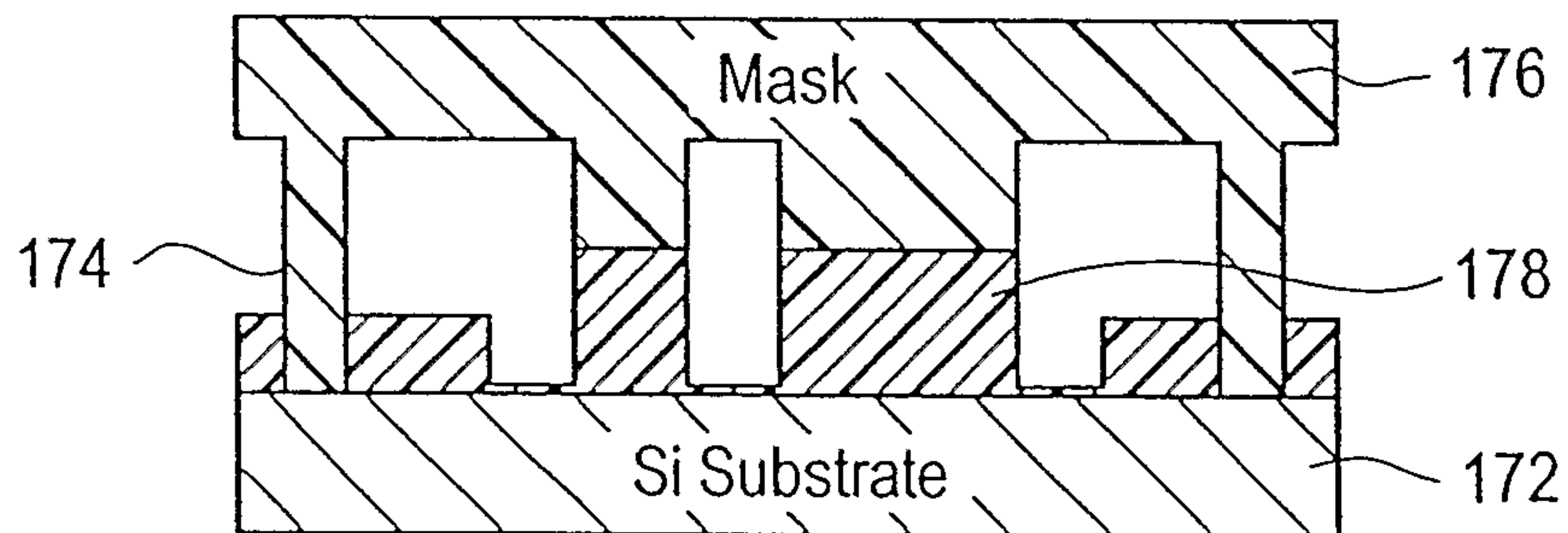


FIG. 10C

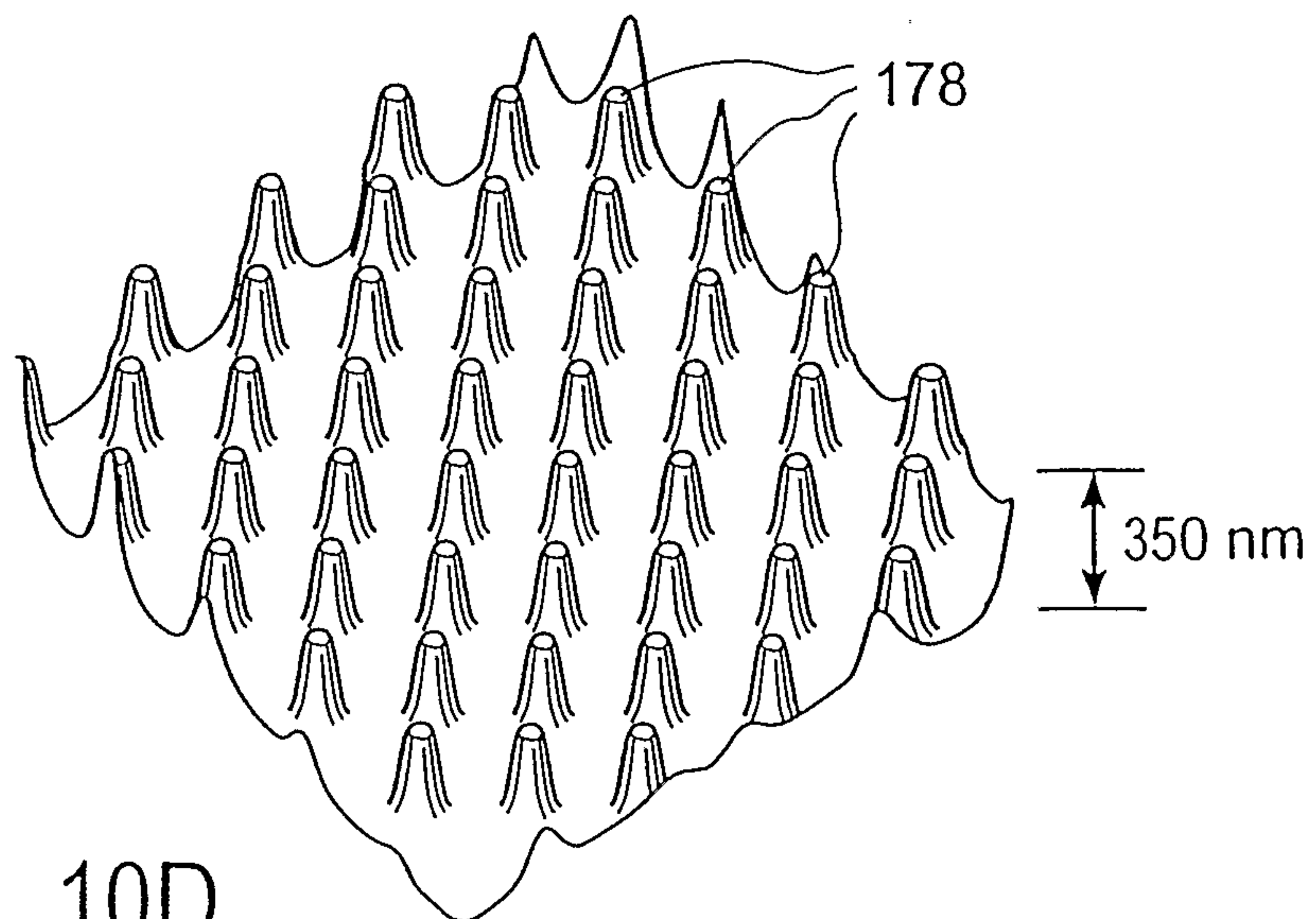


FIG. 10D

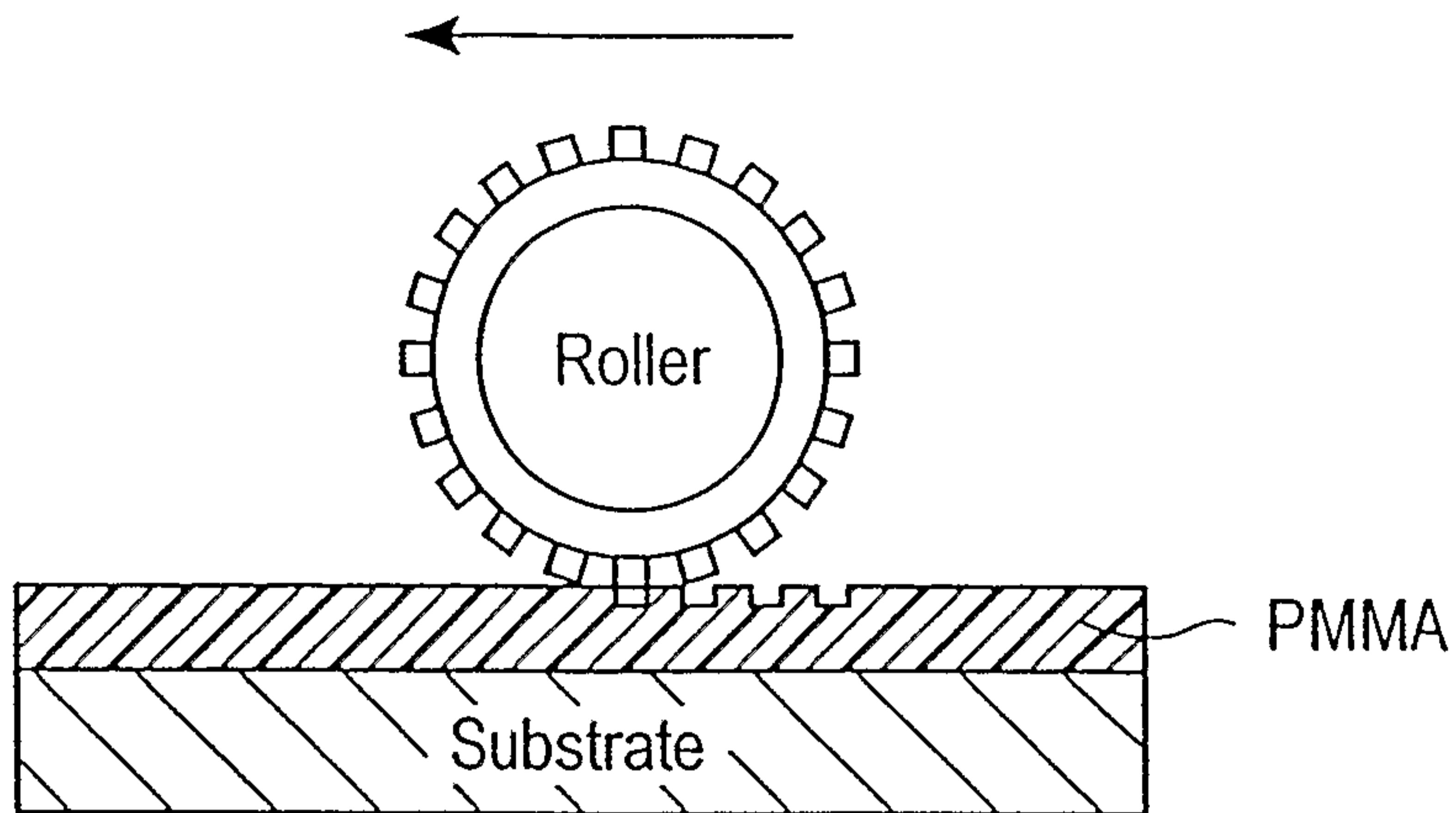


FIG. 11A

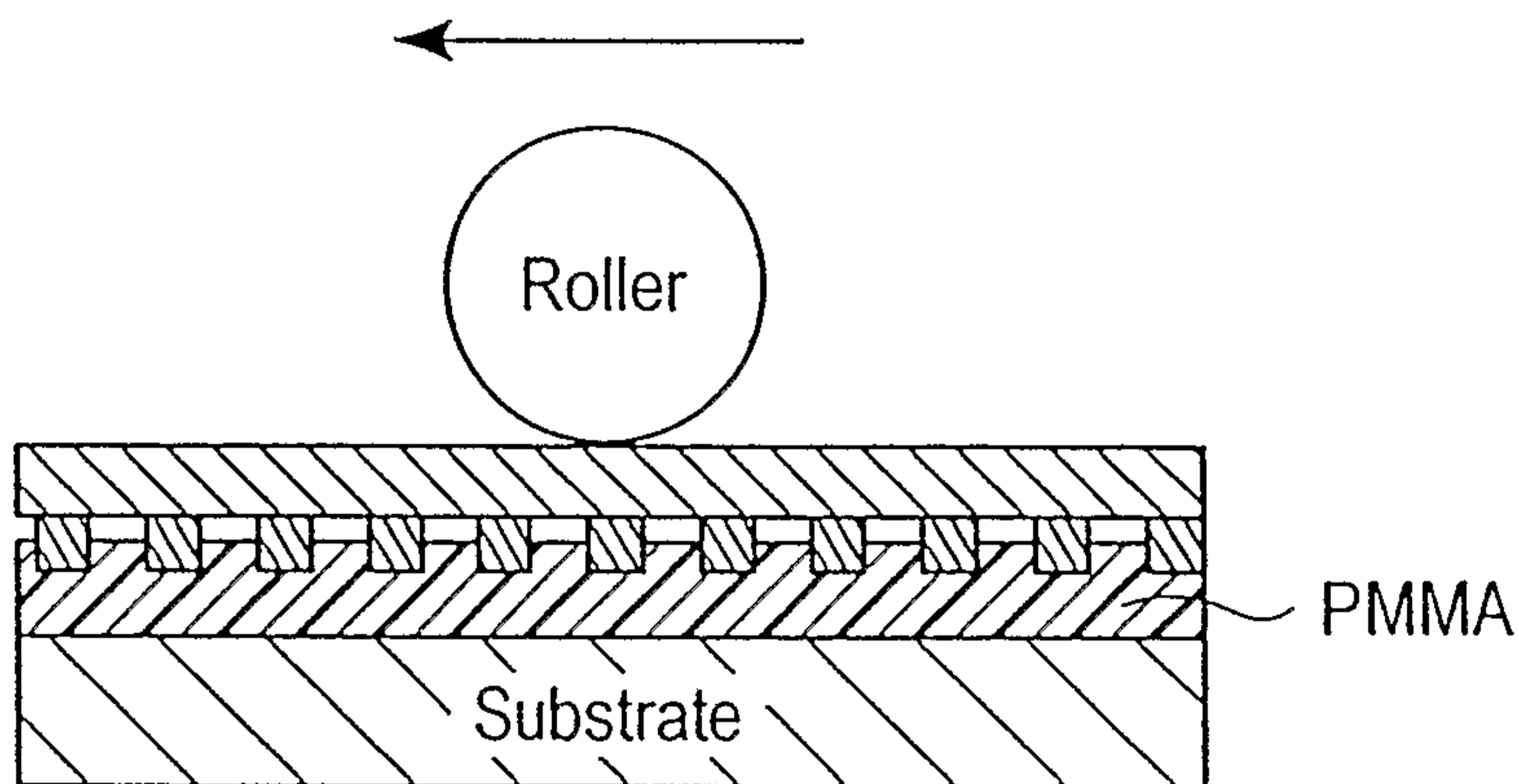


FIG. 11B

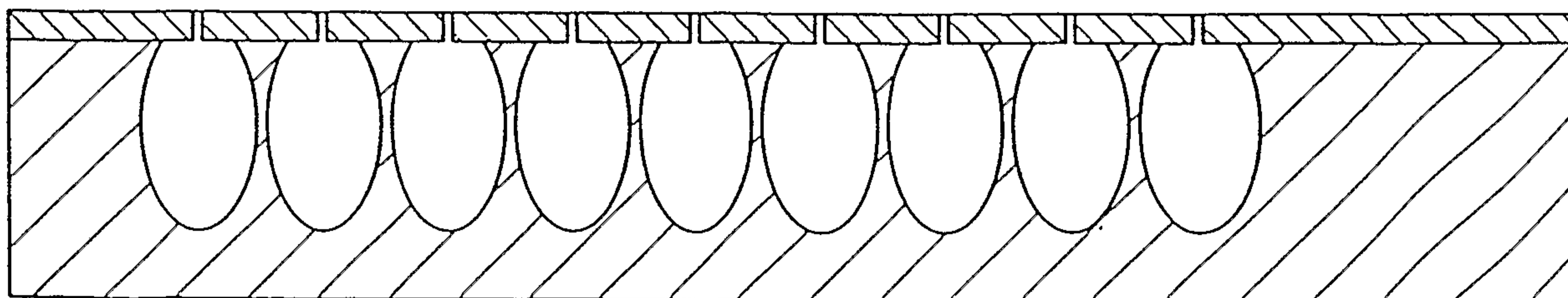


FIG. 12

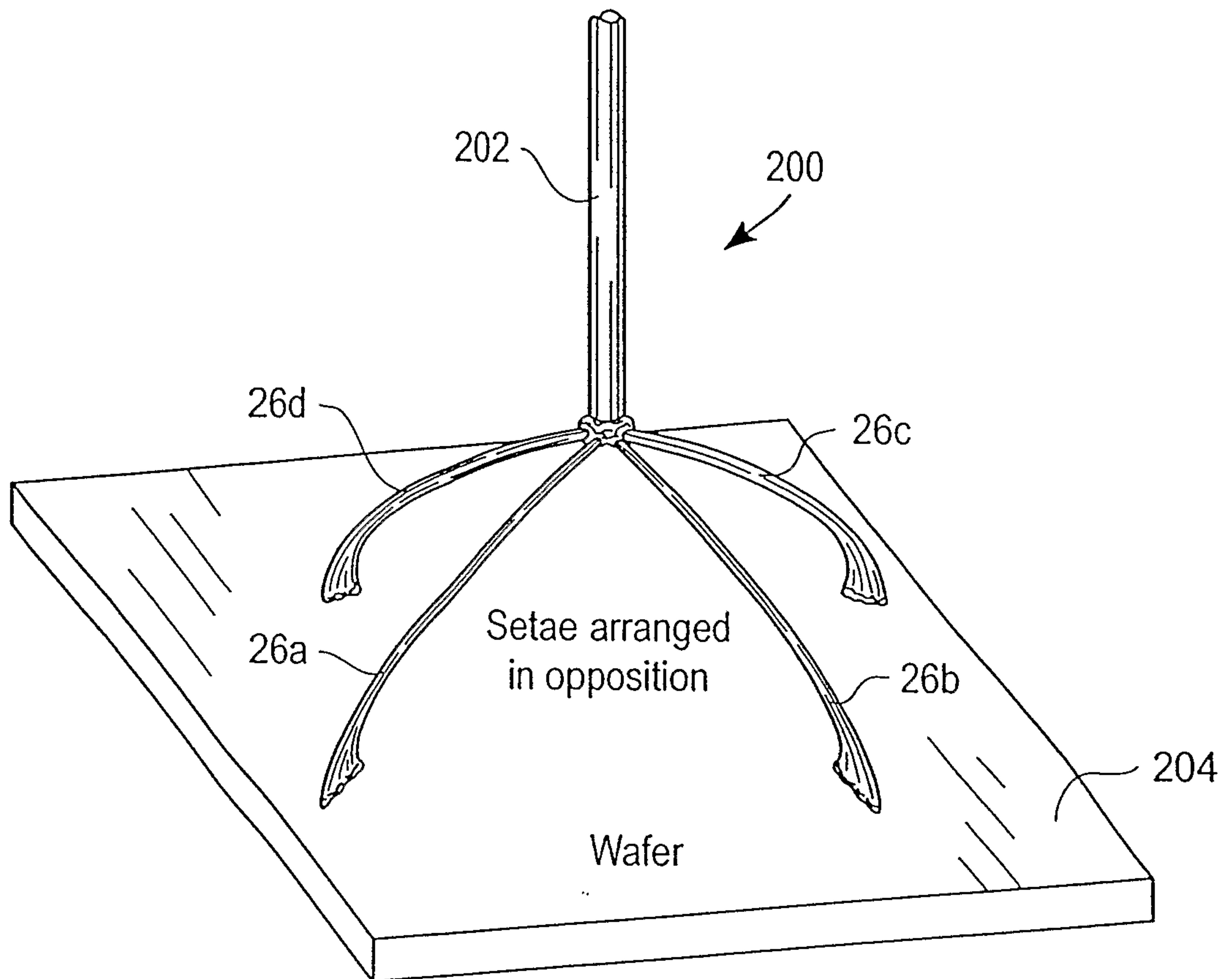


FIG. 13

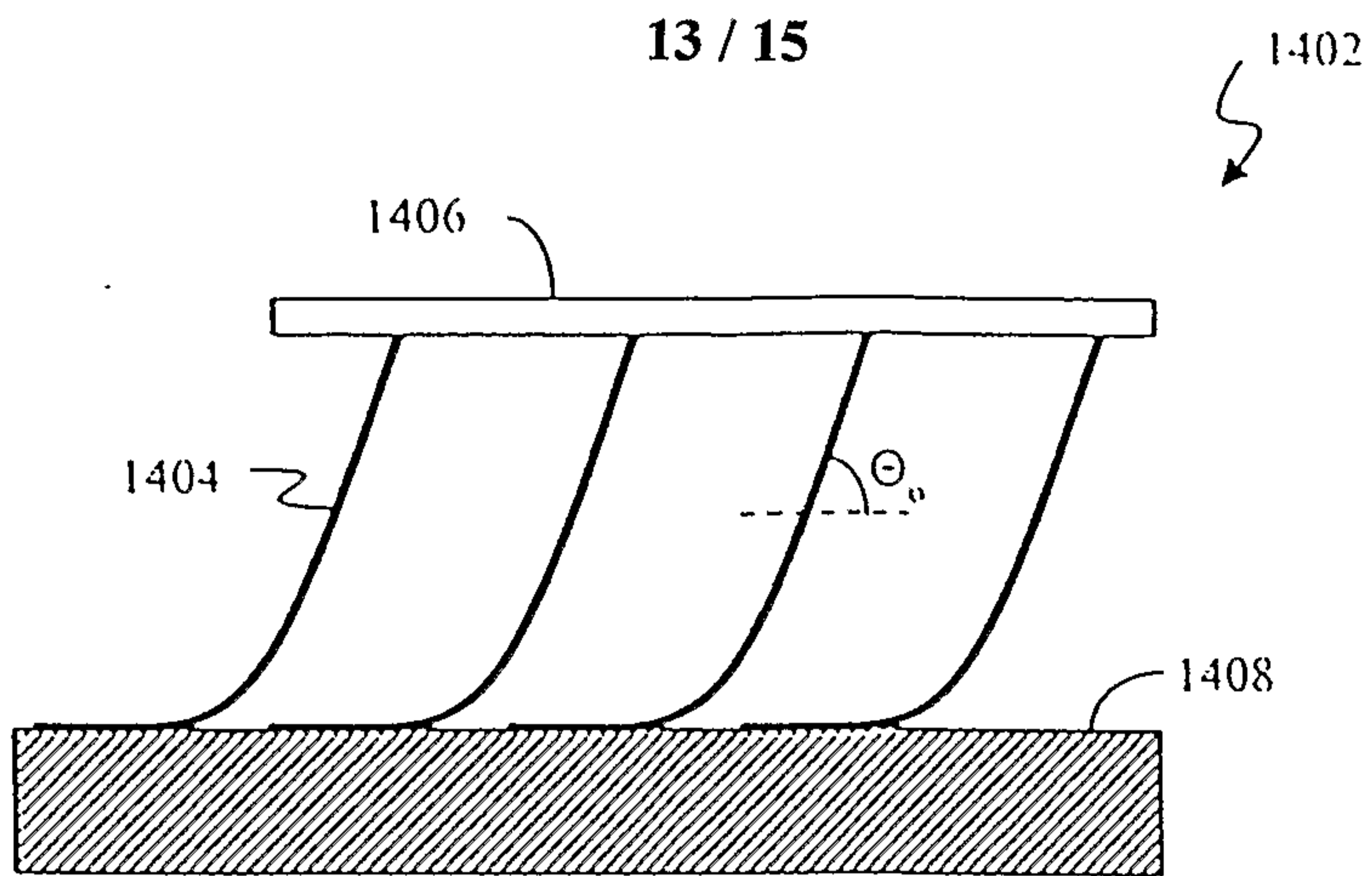


FIG. 14

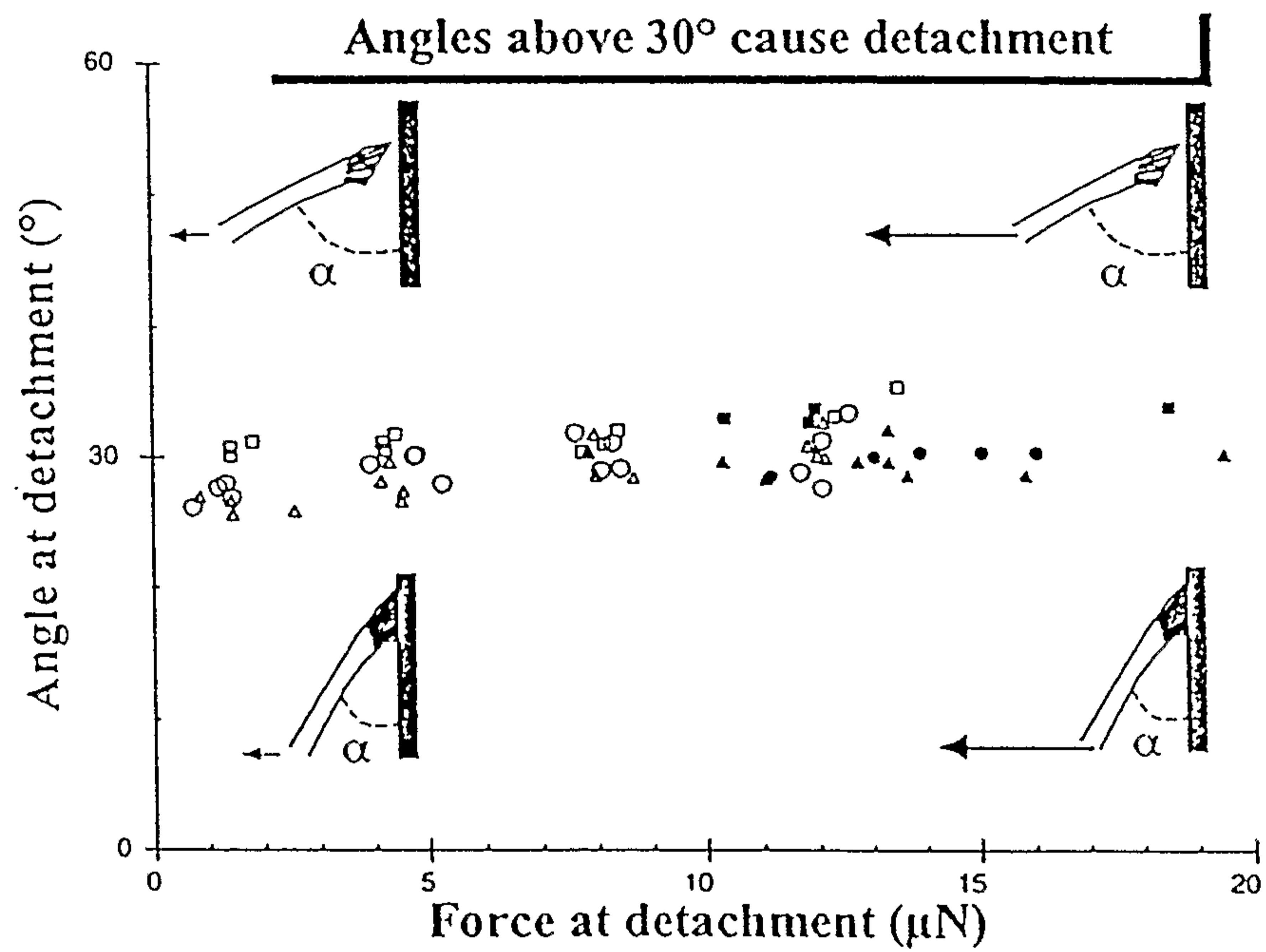


FIG. 15



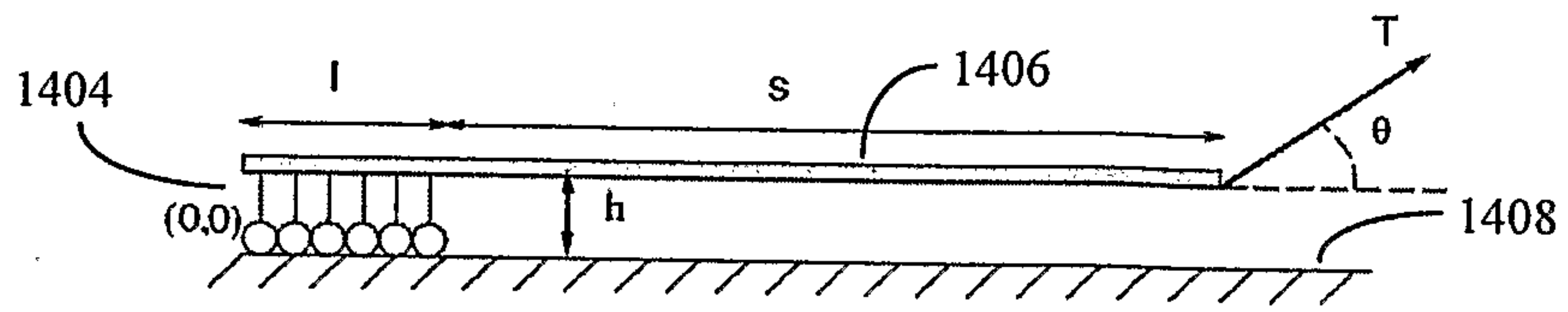


FIG. 16

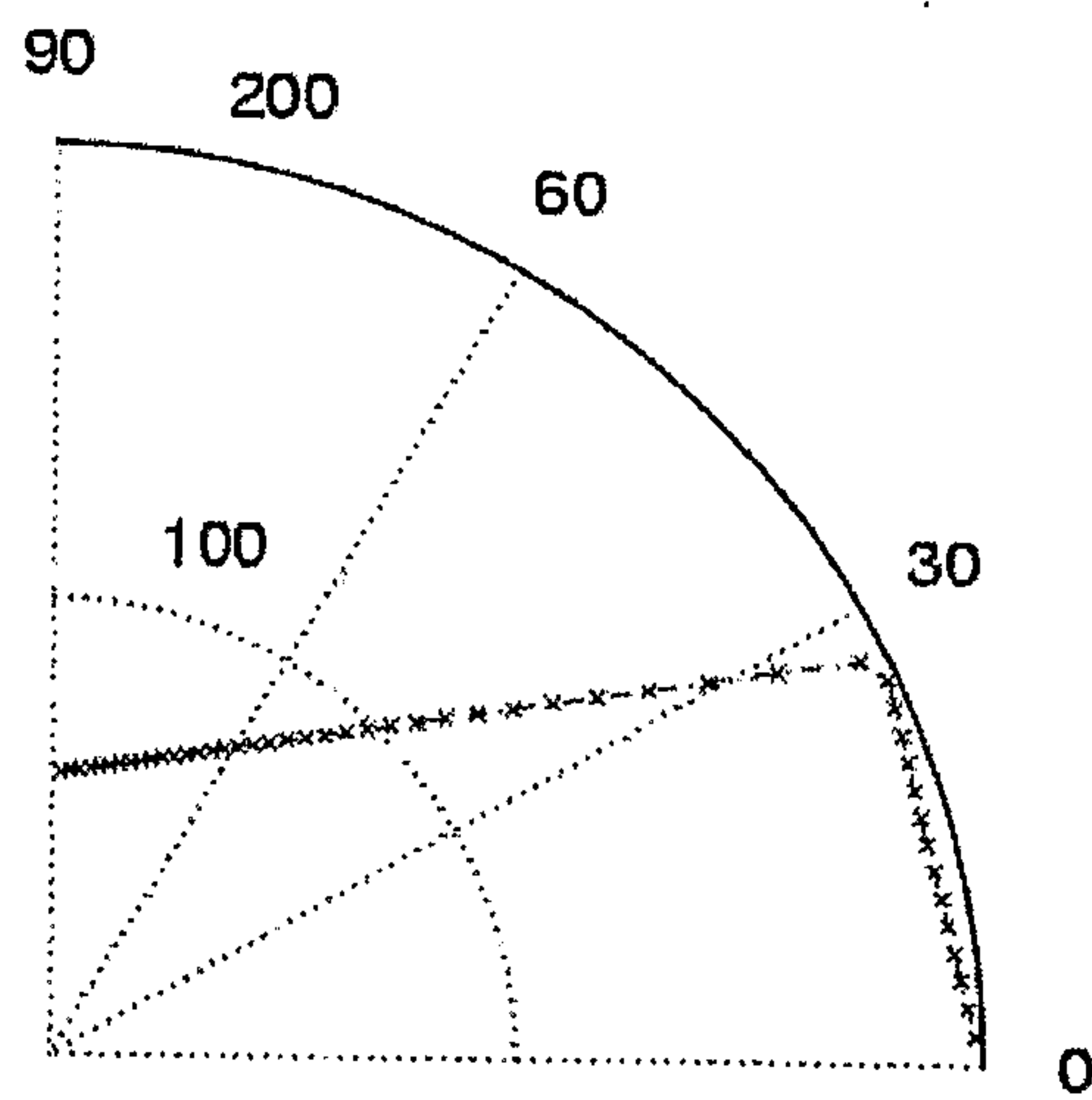


FIG. 17

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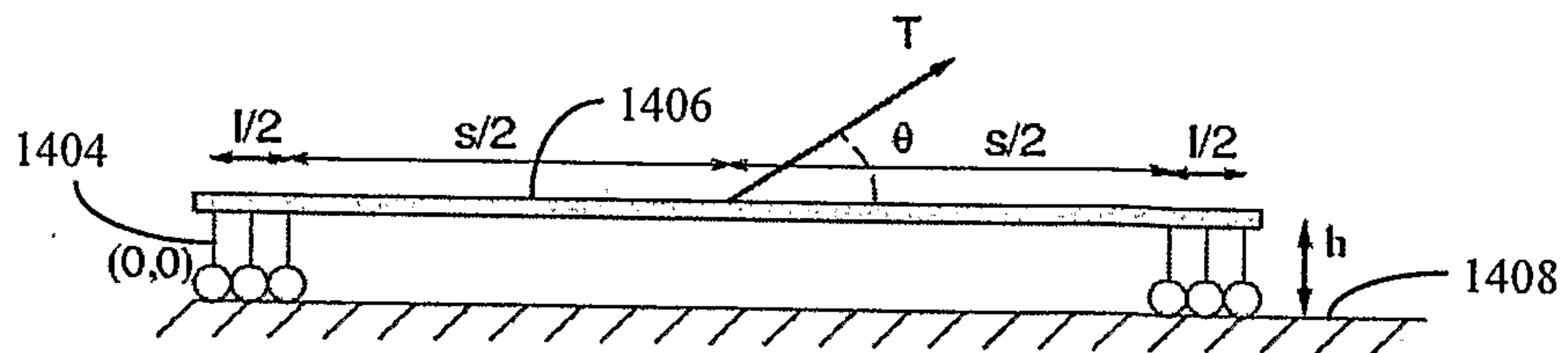


FIG. 18

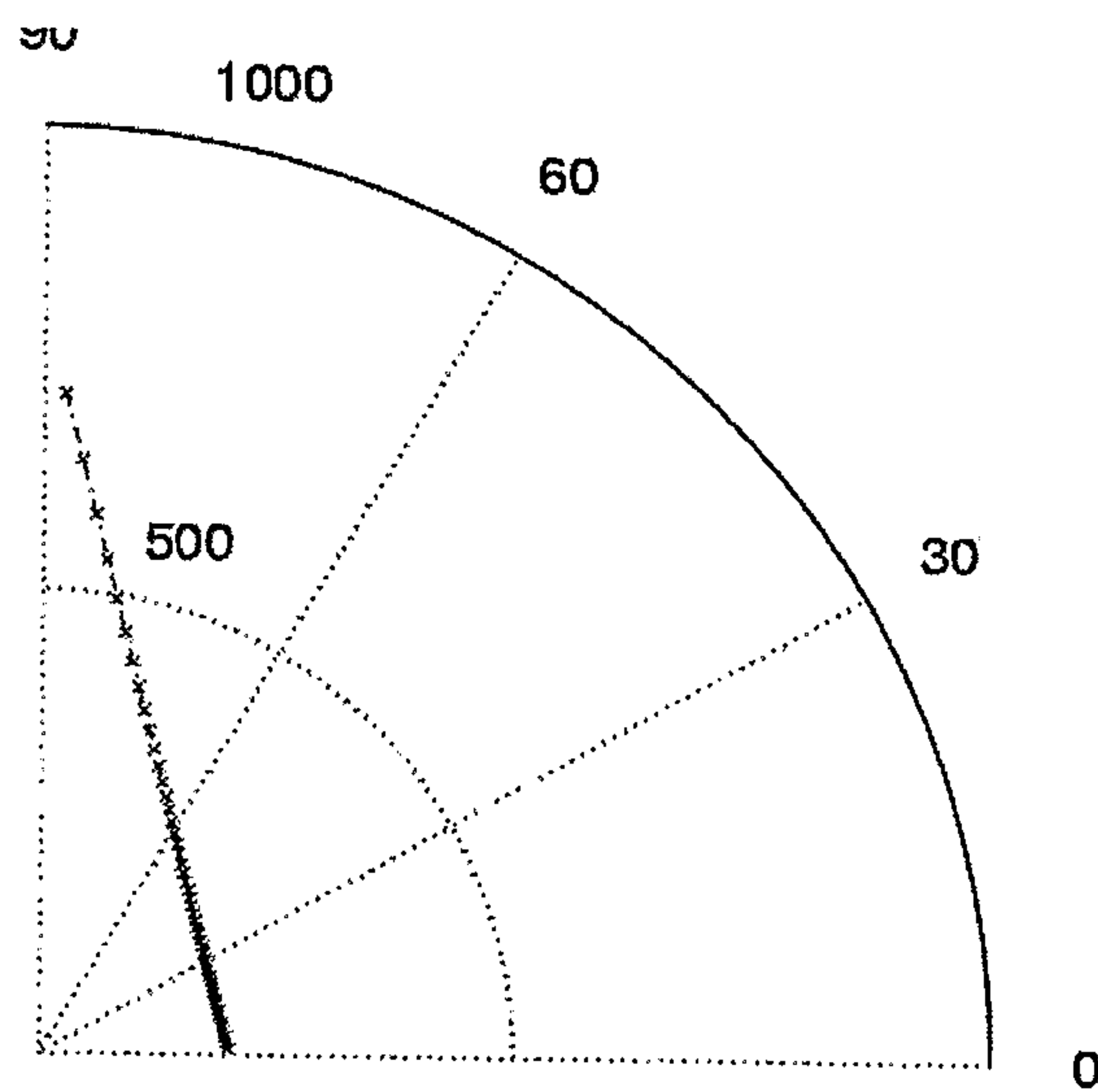


FIG. 19

